EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	106	((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08
S2	15	((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane))	USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:00
S 3	93	S1 and (@ad<="20040416" or @prad<="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:01
S4	21	(("20050233933") or ("20060033071") or ("20060019857") or ("20060022166") or ("20060043330") or ("20060025322") or ("6270689") or ("6649079") or ("20030178597") or ("20040256594") or ("20050233923") or ("6843930") or ("20040021124") or ("5562861") or ("5444102") or ("6526764") or ("20050230657") or ("5674451") or ("5611210") or ("5685915") or ("6875370")).PN.	US-PGPUB; USPAT	OR	OFF	2006/03/02 13:01
S5	14	S4 and (@ad<="20040416" or @prad<="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:07
S6	2	S4 and (@ad="20040416" or @prad="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08
S7	0	S6 and ((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08

3/2/06 4:45:17 PM Page 1

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Welcome to STN International! Enter x:x
LOGINID:ssspta1751gxw
PASSWORD:
TERMINAL (ENTER 1, 2, 3, OR ?):2

* * * * * * * * * * * * Welcome to STN International
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NEWS 1
                 Web Page URLs for STN Seminar Schedule - N. America
NEWS 2
                 "Ask CAS" for self-help around the clock
NEWS 3 DEC 05
                 CASREACT(R) - Over 10 million reactions available
NEWS 4 DEC 14
                 2006 MeSH terms loaded in MEDLINE/LMEDLINE
NEWS 5 DEC 14 2006 MeSH terms loaded for MEDLINE file segment of TOXCENTER
NEWS 6 DEC 14 CA/CAplus to be enhanced with updated IPC codes
NEWS 7 DEC 21 IPC search and display fields enhanced in CA/CAplus with the
                 IPC reform
         DEC 23
                New IPC8 SEARCH, DISPLAY, and SELECT fields in USPATFULL/
NEWS
                 IPC 8 searching in IFIPAT, IFIUDB, and IFICDB
NEWS 9 JAN 13
NEWS 10 JAN 13
                New IPC 8 SEARCH, DISPLAY, and SELECT enhancements added to
                 INPADOC
NEWS 11 JAN 17
                Pre-1988 INPI data added to MARPAT
NEWS 12
        JAN 17
                IPC 8 in the WPI family of databases including WPIFV
NEWS 13
        JAN 30
                Saved answer limit increased
NEWS 14 JAN 31
                Monthly current-awareness alert (SDI) frequency
                 added to TULSA
NEWS 15 FEB 21 STN AnaVist, Version 1.1, lets you share your STN AnaVist
                 visualization results
NEWS 16 FEB 22 Status of current WO (PCT) information on STN
NEWS 17 FEB 22 The IPC thesaurus added to additional patent databases on STN
NEWS 18 FEB 22 Updates in EPFULL; IPC 8 enhancements added
NEWS 19 FEB 27 New STN AnaVist pricing effective March 1, 2006
NEWS 20 FEB 28 MEDLINE/LMEDLINE reload improves functionality
NEWS 21 FEB 28
                TOXCENTER reloaded with enhancements
NEWS 22 FEB 28
                REGISTRY/ZREGISTRY enhanced with more experimental spectral
                 property data
NEWS 23 MAR 01
                INSPEC reloaded and enhanced
NEWS EXPRESS FEBRUARY 15 CURRENT VERSION FOR WINDOWS IS V8.01a,
              CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
             AND CURRENT DISCOVER FILE IS DATED 19 DECEMBER 2005.
              V8.0 AND V8.01 USERS CAN OBTAIN THE UPGRADE TO V8.01a AT
             http://download.cas.org/express/v8.0-Discover/
              STN Operating Hours Plus Help Desk Availability
NEWS HOURS
NEWS INTER
             General Internet Information
NEWS LOGIN
             Welcome Banner and News Items
NEWS PHONE
             Direct Dial and Telecommunication Network Access to STN
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Enter NEWS followed by the item number or name to see news on that specific topic.

NEWS WWW

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CAS World Wide Web Site (general information)

=> s difluoroethane/cn

THIS COMMAND NOT AVAILABLE IN THE CURRENT FILE
Some commands only work in certain files. For example, the EXPAND
command can only be used to look at the index in a file which has an
index. Enter "HELP COMMANDS" at an arrow prompt (=>) for a list of

commands which can be used in this file.

=> file req

COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION

FULL ESTIMATED COST

0.21 SESSION 0.21 0.21

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2006 American Chemical Society (ACS)

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STRUCTURE FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9 DICTIONARY FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006

Please note that search-term pricing does apply when conducting SmartSELECT searches.

* The CA roles and document type information have been removed from * the IDE default display format and the ED field has been added, *

* effective March 20, 2005. A new display format, IDERL, is now *
* available and contains the CA role and document type information. *

* ********************************

Structure search iteration limits have been increased. See HELP SLIMITS for details.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

http://www.cas.org/ONLINE/UG/regprops.html

=> s difluoroethane/cn

L1 1 DIFLUOROETHANE/CN

=> s trifluoromethyl iodide/cn

L2 1 TRIFLUOROMETHYL IODIDE/CN

=> file caplus, uspatful COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION 9.96 10.17

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 11:33:34 ON 02 MAR 2006
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
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FILE 'USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
CA INDEXING COPYRIGHT (C) 2006 AMERICAN CHEMICAL SOCIETY (ACS)

```
=> s l1 and l2
L3
           0 L1 AND L2
=> s l1
L4
          214 L1
=> s 12
L5
         2027 L2
=> s 14 and 15
            0 L4 AND L5
1.6
=> file reg
COST IN U.S. DOLLARS
                                               SINCE FILE
                                                              TOTAL
                                                            SESSION
                                                    ENTRY
FULL ESTIMATED COST
                                                     1.97
                                                              12.14
FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2006 American Chemical Society (ACS)
Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.
STRUCTURE FILE UPDATES:
                          1 MAR 2006 HIGHEST RN 875609-25-9
DICTIONARY FILE UPDATES:
                          1 MAR 2006 HIGHEST RN 875609-25-9
New CAS Information Use Policies, enter HELP USAGETERMS for details.
TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006
  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.
*********************
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added,
* effective March 20, 2005. A new display format, IDERL, is now
* available and contains the CA role and document type information.
************
Structure search iteration limits have been increased. See HELP SLIMITS
for details.
REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document. For information
on property searching in REGISTRY, refer to:
http://www.cas.org/ONLINE/UG/regprops.html
=> d his
     (FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)
    FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006
L1
             1 S DIFLUOROETHANE/CN
L2
             1 S TRIFLUOROMETHYL IODIDE/CN
    FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
             0 S L1 AND L2
L3
           214 S L1
L4
L5
          2027 S L2
             0 S L4 AND L5
L6
```

```
=> d l1
1.1
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
     25497-28-3 REGISTRY
RN
     Entered STN: 16 Nov 1984
ED
CN
     Ethane, difluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
     Difluoroethane
CN
MF
     C2 H4 F2
CI
     IDS, COM
LC
                  BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMLIST, CIN, DETHERM*,
     STN Files:
       ENCOMPLIT, ENCOMPLIT2, ENCOMPPAT, ENCOMPPAT2, IFICDB, IFIPAT, IFIUDB,
       NIOSHTIC, PDLCOM*, PIRA, PROMT, TOXCENTER, TULSA, USPAT2, USPATFULL, VTB
          (*File contains numerically searchable property data)
1/2 H<sub>3</sub>C-CH<sub>3</sub>
     D1-F
**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**
             164 REFERENCES IN FILE CA (1907 TO DATE)
             164 REFERENCES IN FILE CAPLUS (1907 TO DATE)
               3 REFERENCES IN FILE CAOLD (PRIOR TO 1967)
=> d 12
L2
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
RN
     2314-97-8 REGISTRY
ED
     Entered STN: 16 Nov 1984
     Methane, trifluoroiodo- (6CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
    Freon 13I1
CN
     Iodotrifluoromethane
CN
     Monoiodotrifluoromethane
CN
     Perfluoromethyl iodide
CN
    R 13I1
CN
     Trifluoroiodomethane
CN
     Trifluoromethyl iodide
FS
     3D CONCORD
DR
     263005-66-9
     C F3 I
MF
CI
     COM
LC
     STN Files:
                  BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS,
       CHEMINFORMRX, CHEMLIST, CHEMSAFE, CIN, CSCHEM, CSNB, DETHERM*, DIPPR*,
       GMELIN*, IFICDB, IFIPAT, IFIUDB, MEDLINE, MSDS-OHS, PROMT, PS, RTECS*,
       SPECINFO, TOXCENTER, ULIDAT, USPAT2, USPATFULL, VTB
         (*File contains numerically searchable property data)
     Other Sources:
                     EINECS**, NDSL**, TSCA**
         (**Enter CHEMLIST File for up-to-date regulatory information)
```

- 1837 REFERENCES IN FILE CA (1907 TO DATE)
 - 12 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
- 1839 REFERENCES IN FILE CAPLUS (1907 TO DATE)
 - 88 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> d his

L1

L2

L3

(FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006

1 S DIFLUOROETHANE/CN

1 S TRIFLUOROMETHYL IODIDE/CN

FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006

0 S L1 AND L2

L4 214 S L1

L5 2027 S L2

L6 0 S L4 AND L5

FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006

=> d 14 ti,pi

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

- L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PA	CENT :	NO.	*		KIN	D	DATE			APPL	ICAT	ION :	NO.		D?	ATE	
				-			-											
ΡI	US	2005	2777	01		A1		2005	1215		US 2	004-	8684	00		20	0040	615
	WO	2006	0020	43		A 1		2006	0105	•	WO 2	005-1	US20	929		20	0050	614
		W:	ΑE,	AG,	AL,	AM,	AT,	ΑU,	AZ,	BA,	BB,	BG,	BR,	BW,	BY,	BZ,	CA,	CH,
								DE,										
								ID,										
								LU,										
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				ZM,		•	•		,	,	,	,	,	,	,	,	,	10,
		RW:	AT.	BE.	BG.	CH.	CY.	CZ,	DE.	DK.	EE.	ES.	FT.	FR	GB	GR	нп	TE
								NL,										
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			nΔ,	, עניו	ĸυ,	ΤJ,	∓ I^I											

=> d l4 ti,pi 1-

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

YOU HAVE REQUESTED DATA FROM 214 ANSWERS - CONTINUE? Y/(N):y

- L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT	NO.			KIN	D	DATE			APPL	ICAT	ION :	NO.		D	ATE	
						-					- -	- -			-	- -	-
PΙ	US 2005	27770)1		A1		2005	1215	1	US 2	004-	8684	00		2	0040	615
	WO 2006	00204	13		A 1		2006	0105	1	WO 2	005-1	US20	929		2	0050	614
	₩:	ΑE,	AG,	AL,	AM,	ΑT,	AU,	AZ,	BA,	BB,	BG,	BR,	BW,	BY,	BZ,	CA,	CH.
		CN,	CO,	CR,	CU,	CZ,	DE,	DK,	DM,	DZ,	EC,	EE,	EG.	ES,	FI.	GB.	GD.
							ID,										
							LU,										

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SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU,
            ZA, ZM, ZW
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG,
            KZ, MD, RU, TJ, TM
    ANSWER 2 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Procedure for processing hollow glassware, particularly a bottle
TI
                 KIND DATE APPLICATION NO.
    PATENT NO.
                                          ______
                                                                _____
                              _____
                        _ _ _ _
                                        AT 2003-941
                        A5
                              20040615
                                                                20030617
    AT 200300941
ΡI
                        В
                              20050125
    AT 412341
    ANSWER 3 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation method and equipment of difluorochloroethane
ΤI
                       KIND DATE APPLICATION NO.
                                                                DATE
                              _____
                                          -----
                                                                _ _ _ _ _ _
    _____
                        ----
                                          CN 2004-10015778
                                                                20040109
                        Α
                              20041222
PΙ
    CN 1556083
    ANSWER 4 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant composition with lubricant
ΤI
                       KIND DATE APPLICATION NO.
                                                               DATE
    PATENT NO.
                                         -----
                              _____
                        ----
     ______
                              20050512 WO 2004-US34724
                                                               20041020
    WO 2005042679
                        A1
PΙ
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
            TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN. TD. TG
                                          US 2004-969621
                                                                20041020
    US 2005109977
                         A1
                               20050526
    ANSWER 5 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Closed cycle refrigeration system and mixed component refrigerant
TI
    PATENT NO. KIND DATE APPLICATION NO. DATE
                        ----
                              _____
                                          ______
                                                                ----<del>---</del>
    ______
                              20050428
                                          US 2003-694699
                                                                20031028
ΡI
    US 2005086950
                        A1
    ANSWER 6 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Improvements in or relating to aerosol formulations comprising formoterol
TI
    fumarate dihydrate
                       KIND DATE APPLICATION NO.
    PATENT NO.
     ______
                       ----
                              _____
                                          ______
                                                                _____
                      A2
A3
    WO 2005034927
                                         WO 2004-IB3465
                                                                20041008
                              20050421
PΙ
                              20050602
    WO 2005034927
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
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            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN, TD, TG
    ANSWER 7 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Consolidation heat treating atmospheres for manufacture of sol-gel-derived
ΤI
    halogen-doped optical glass
                                          APPLICATION NO.
                                                                DATE
                        KIND
    PATENT NO.
                             DATE
```

NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK,

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A1
                              20041007
                                         US 2004-771176
PΙ
    US 2004194511
                       A1
                              20030807
                                         US 2002-62748
                                                                20020201
    US 2003147605
    US 6928220
                        B2
                              20050809
                                                                20020807
                        A1
                              20030807
                                         US 2002-215162
    US 2003147606
    ANSWER 8 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Polyol compositions containing polyether or polyester polyols and
TΙ
    polyisocyanate-based foams prepared therefrom
                  KIND DATE APPLICATION NO.
    PATENT NO.
    EP 1435366 A1 20040707 EP 2003-250046
                                                               20030103
PΙ
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                              20040729 CA 2003-2511811 20031223
                        AA
    CA 2511811
                                                               20031223
                        A1
                              20040729
                                         WO 2003-US41607
    WO 2004063243
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            HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT,
            LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,
            RO, RU, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US,
            UZ, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
            BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
            ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
            TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
                              20051101 BR 2003-17211
                                                               20031223
    BR 2003017211
                        Α
    ANSWER 9 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Materials and methods for the conversion of hydrofluorocarbons to
ΤI
    fluoromonomers
    US 2004127757 A1 2004127
                                       APPLICATION NO.
                                                               DATE
                                                               -----
                                         -----
                      A1 20040701 US 2002-331821 20021230
AA 20040722 CA 2003-2511887 20031230
ΡI
    WO 2004060842 A1 20040722
WO 2004060842 C1 20041021
                                       WO 2003-US41851
                                                               20031230
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
            PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,
            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
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            TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD,
                             20051005 EP 2003-815021
    EP 1581468
                        A1
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                                         US 2005-218055
    US 2005288536
                        A1
                              20051229
    ANSWER 10 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Plasma device and procedure for anisotropic etching in of structures in a
ΤI
    substrate
                      KIND DATE
    PATENT NO.
                                       APPLICATION NO.
                      ---- ------
                                         _____
                       A1
    DE 10247913
                              20040422 DE 2002-10247913 20021014
ΡI
                       A2 20040429
                                        WO 2003-DE2971
                                                               20030909
    WO 2004036627
                           20040722
    WO 2004036627
                        A3
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            IT, LU, MC, NL, PT, RO, SE, SI, SK, TR
                        A2
                             20050720 EP 2003-753277
    EP 1554747
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    JP 2006503425
                        T2
                              20060126
                                        JP 2004-543938
                                                               20030909
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Procedure for the plasma anisotropic etching of a silicon substrate
ΤI
    PATENT NO.
                       KIND
                              DATE APPLICATION NO.
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                                         DE 2002-10246063
    DE 10246063
                              20040422
                                                                20021002
ΡI
                        A1
    ANSWER 12 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Method for plasma etching performance enhancement in semiconductor device
TI
    fabrication
                                        APPLICATION NO.
    PATENT NO.
                      KIND DATE
                                                               DATE
    US 2004072443 A1 20040415 US 2002-295601
                                                                _____
                                                                20021114
PΙ
    US 6833325 B2 20041221

US 2004072430 A1 20040415 US 2003-674675 20030929

WO 2004034445 A2 20040422 WO 2003-US31712 20031006

WO 2004034445 A3 20040812

WO 2004034445 B1 20040930
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
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            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
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            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
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            FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR,
            BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
    AU 2003282718 A1 20040504 AU 2003-282718 20031006 EP 1550153 A2 20050706 EP 2003-774602 20031006
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
    US 2005037624
                        A1
                             20050217
                                         US 2004-946181
                                                                20040920
L4
    ANSWER 13 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
    Method for etching photolithographic reticles
    PATENT NO. KIND DATE APPLICATION NO. DATE
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                                         ______
    JP 2004038154 A2
                              20040205 JP 2003-136222
                                                              20030514
PΙ
                                       US 2003-437729
    US 2004072081
                       A1
                             20040415
    ANSWER 14 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Safety tires having good durability and riding comfort
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
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                              _____
PΙ
    JP 2003118311
                       A2
                              20030423 JP 2002-94474
                                                               20020329
    ANSWER 15 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤТ
    Silicon dioxide etching yield measurements with inductively coupled
    fluorocarbon plasmas
    ANSWER 16 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Speed-of-sound, ideal-gas heat capacity, and second acoustic virial
TI
    coefficient for mixing refrigerant difluoroethane (HFC152a) +
    difluoromethane (HCFC22)
    ANSWER 17 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Resistive plate chambers for muon detection at LHC
ΤI
    ANSWER 18 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Heat transfer fluids useable for cooling items, such as optical fibers
TΙ
    PATENT NO. KIND DATE APPLICATION NO. DATE
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                       _ - - -
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    WO 2002074709
PΙ
                       A1 20020926 WO 2002-EP3030
                                                               20020314
        W: AU, BR, CN, IN, JP
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                                        EP 2002-753572
    EP 1373153
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
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                              20040512 CN 2002-806445
    CN 1496340
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US 2004-874079
                                                             20040622
    US 2004227125 A1
                             20041118
    US 2005218371
                       A1
                             20051006
                                       US 2005-130331
                                                             20050517
    ANSWER 19 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Algorithmically Compressed Data and the Topological Conjecture for the
    Inner-Core Electrons
    ANSWER 20 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Substrate cleaning apparatus and method
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
                                                           DATE
    US 2002072016 A1 20020613 US 2000-737373
US 6692903 P2 20040017
                                                            -----
                                                            20001213
    US 6692903 B2 20040217

WO 2002049078 A2 20020620 WO 2001-US48273

WO 2002049078 A3 20021024
                                                            20011210
        W: CN, JP, KR, SG
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
           PT, SE, TR
    ANSWER 21 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Hydrocarbon-based refrigerant mixture composition for replacing R-12 and
    R-22 refrigerants
                      KIND DATE APPLICATION NO.
    PATENT NO.
                                                           DATE
                                       ______
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                             20000705 KR 2000-17251
                                                            20000403
    KR 2000036953
                      Α
    ANSWER 22 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Formulations of mometasone and a bronchodilator for pulmonary
    administration
                     KIND DATE
                                      APPLICATION NO.
                                                           DATE
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    WO 2002011711
                     A2 20020214 WO 2001-US24093 20010801
                  A3 20030227
B1 20040422
    WO 2002011711
    WO 2002011711
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
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           GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
           LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT,
           RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ,
           VN, YU, ZA, ZW
        RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AM, AZ, BY, KG,
           KZ, MD, RU, TJ, TM, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR,
           IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN,
           GQ, GW, ML, MR, NE, SN, TD, TG
               AA 20020214
                                       CA 2001-2417973
    CA 2417973
                                                           20010801
    AU 2001078115
                      A5
                             20020218
                                     AU 2001-78115
                      A1 20020620 US 2001-920340
A2 20030521 EP 2001-956079
                             20020620 US 2001-920340
    US 2002076382
    EP 1311294
           AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
    US 2004198708
                      A1
                           20041007
                                     US 2004-824711
                                                            20040414
    ANSWER 23 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Detection of fluorine containing gas compounds
    PATENT NO. KIND DATE APPLICATION NO. DATE
                      ____
                                       _____
                            20020123 JP 2000-209708
    JP 2002022725
                      A2
                                                           20000711
                      B2
    JP 3640601
                            20050420
    ANSWER 24 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Additivity of the Correlation Energy in Some 3D Organic Molecules
    ANSWER 25 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Fluorohydrocarbon etchant with selectivity for doped silicon dioxide over
    undoped silicon dioxide and silicon nitride, processes which employ the
    etchant, and structures formed thereby
    PATENT NO. KIND DATE APPLICATION NO. DATE
    WO 2002003439 A2 20020110 WO 2001-US41275
                                                           20010705
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WO 2002003439 A3
WO 2002003439 C1
                    A3 20020606
C1 20020704
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                     A2 20030402 EP 2001-956164
                                                               20010705
EP 1297564
        AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
        IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
                            20040129 JP 2002-507425
                                                               20010705
JP 2004503082
                     T2
ANSWER 26 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Fabrication of electric circuits by reactive-gas etching of masked metal
layers on substrates
                                      APPLICATION NO.
PATENT NO. KIND
                           DATE
                                        _____. ·
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                                                                _____
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WO 2001096955 A2
                            20011220 WO 2001-US19282 20010615
                    A3
                            20021128
WO 2001096955
    W: JP, US
    RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
        PT, SE, TR
                                                                20010615
EP 1290495
                     A2
                            20030312 EP 2001-946420
    R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
        IE, FI, CY, TR
                                        JP 2002-511020
JP 2004503829
                     T2
                            20040205
                                                                20010615
                                        US 2001-24958
US 2003003374
                     A1
                            20030102
                                                                20011218
ANSWER 27 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
High-density plasma etching of carbon-based low-k materials in an
integrated circuit
                          DATE APPLICATION NO.
PATENT NO.
                    KIND
                                                               -----
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                                       _____
US 6284149
                           20010904 US 1998-156956 19980918
                    B1
ANSWER 28 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Flower-like capacitor structure for a memory cell
PATENT NO. KIND DATE APPLICATION NO. DATE
                                        -----
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                            -----
US 6281542
                    B1
                            20010828 US 1999-249840 19990215
                           19991026 US 1998-60565
                                                               19980414
US 5973350
                    Α
ANSWER 29 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Apparatus for providing ozonated process fluid and methods for using same
PATENT NO. KIND DATE APPLICATION NO. DATE
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                    - - - <del>-</del>
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                                       ______
WO 2001040124 A1 20010607 WO 2000-US42449 WO 2001040124 C2 20020808
                                                               20001201
    W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
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        HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT,
        LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU,
        SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU,
        ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM
    RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY,
        DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF,
        BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
US 2002066717 A1 20020606 US 2000-727661 20001201
                            20020611
                                       TW 2000-89125686
                                                               20010108
TW 490757
                     В
ANSWER 30 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Cooling agent
                   KIND DATE APPLICATION NO.
                                                               DATE
PATENT NO.
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                                                                _____
                           19990827 RU 1997-120359
                     C1
                                                               19971210
RU 2135541
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- L4 ANSWER 31 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- Fluoroethane etchant with selectivity for doped silicon dioxide over TI undoped silicon dioxide and silicon nitride, processes which employ the etchant, and structures formed for semiconductor devices

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
		- -			
ΡI	US 6117791	Α	20000912	US 1998-102152	19980622
	US 6537922	B1	20030325	US 2000-625144	20000725
	US 6875371	B1	20050405	US 2000-711324	20001113
	US 2003203639	A1	20031030	US 2003-396164	20030325

- ANSWER 32 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- Evaluation of pentafluoroethane and 1,1-difluoroethane for a dielectric TI etch application in an inductively coupled plasma etch tool
- ANSWER 33 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4

TI	Top	oical	spra	ays (cont	ainii KTNI	ng f	ilm-:	form	ing	pol	Lym	ers	LON 1	NTO.		ח	∆ጥፑ	
	PA.	ENT				KINI	_	DAIE							·		-		
PI	WO	2000	04579	95		A2		2000	0810		WO	20	00-0	3B36	6		2	0000	207
				-				AZ,			BG	.	BR.	BY.	CA.	CH.	CN.	CR.	CU.
		•••						ES,											
								KP,											
							-	MX,											
			SK,	SL,	TJ,	TM,	TR,	TT,	TZ,	UA,	UG	3,	US,	UΖ,	VN,	YU,	ZA,	ZW	
		RW:	GH,	GM,	KE,	LS,	MW,	SD,	SL,	SZ,	TZ	Ζ,	UG,	ZW,	AT,	BE,	CH,	CY,	DE,
								GR,									BF,	ВJ,	CF,
			CG,	CI,	CM,	GΑ,	GN,	GW,	ML,	MR,	NE	Ξ,	SN,	TD,	TG				
	IN	1866 2359	68			Α		2001	1020		IN	19	99-I	3093			1	9990	205
	CA	2359	640			AA		2000	0810		CA	20	00-2	2359	640		2	0000	207
		2000	0244	72		A 5					ΑU	20	00-2	2447	2		2	0000	207
		7595	15			B2		2003											
	BR	2000 1150	00799	97		Α		2001	1030		BR	20	00-	7997			20	0000	207
	EP	1150	661			A2		2001	1107		ΕP	20	00-9	9027	27		20	0000	207
	EP	1150									~-				• • •		~=	wa	
		R:				•		ES,	•	GB,	GF	ζ,	тт,	ъΙ,	ъO,	ΝL,	SE,	MC,	PT,
	TD	2002						RO			TD	20	^^ '	-000			2.	0000	207
	NIZ	2002. 5132	5363. 00	19		12		2002: 2003:							08 08			0000: 0000:	
	NΩ	2132	0 O			F		2003							27			0000	
	DT	2523 1150	60 661			Tr.		2003							27			0000	
	E.C.	2209	812			T3		2004										0000	
		6962	691			B1		2005	1108		US	20	00-5	50384	2 / 1 3		21	0000	
		2000						2000	1221		ZA	20	00-5	5727	1.5		21	0001	
		2001		15		Α		2001										0010	
		1042				A1		2004	0408		HK	20	02-1	10329	95		20	0020	
		20042		14		A1		2004	1028		US	20	03-6	865	17		20	0031	

- ANSWER 34 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- Synthetic lubricating oil-C1-3-hydrofluorocarbon refrigerant combinations ΤI for low-temperature phase separation in refrigeration compressor units

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	WO 2000043464	A1	20000727	WO 1999-US31118	19991228
	W: AU, CA				
	RW: AT, BE, CH,	CY, DE	, DK, ES, F	I, FR, GB, GR, IE, IT,	LU, MC, NL,
	PT, SE				
	US 6374629	B1	20020423	US 1999-236707	19990125
	CA 2360536	AA	20000727	CA 1999-2360536	19991228
	EP 1153099	A1	20011114	EP 1999-968562	19991228

EP 1153099 B1 20040929 R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI

AU 774378 B2 20040624 AU 2000-25954 19991228

- ANSWER 35 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- ΤI Variable load refrigeration system particularly for cryogenic temperatures

	PATENT NO.		DATE		DATE
ΡI	US 6076372	A	20000620	US 1998-222809 MX 1999-11766 ZA 1999-7869	19981230
	US 6076372 MX 9911766	Α	20000731	MX 1999-11766	19991215
	ZA 9907869	A	20000705	ZA 1999-7869	19991223
	CA 2293191	C	20040921	CA 1999-2293191	19991224
	CA 2293191	AA R	20000630	CA 1999-2293191 TW 1999-88123007 EP 1999-126062	19991227
	EP 1016839	A2	20010421	EP 1999-126062	19991228
	EP 1016839	A3	20001102		
	EP 1016839		20030709		
				GB, GR, IT, LI, LU, NL,	SE, MC, PT,
	IE, SI,	LT, LV, FI	, RO	JP 1999-373465	19991228
	TP 3678619	B2	20050803		
	BR 9905991	A	20000905	BR 1999-5991 CN 1999-127429 AT 1999-126062	19991228
	CN 1265462	A	20000906	CN 1999-127429	19991228
	AT 244860	E	20030715	AT 1999-126062	19991228
	ES 2197568	T3	20040101	ES 1999-126062	19991228
	AU 9965541 AU 753979	B2	20000700	AU 1999-65541 US 2000-545670	10001230
	US 6426019	B1	20020730	US 2000-545670	20000407
	US 2003042463	A1	20030306	US 2002-201287	20020724
	US 6881354	B2	20050419		
L4 TI	ANSWER 36 OF 214 A process for di			2006 ACS on STN 1 (CBrF3)	
L4	ANSWER 37 OF 214	. CAPLUS	COPYRIGHT	2006 ACS on STN	
TI				of glass via fiber elong	gation
			_	_	
L4 TI	ANSWER 38 OF 214 Conversion under chlorodifluorome	hydrogen	of dichlo	rodifluoromethane and	
	CHIOLOGILLIAGIOMC	ciidiic over	11101101	2041/202	
L4 TI	ANSWER 39 OF 214 Accidental relea			2006 ACS on STN	
7.4	AMOURD 40 OF 214	CA DI HC	ao ny natai	2006 ACC on CENT	
L4 TI	Cooling agent co			2006 ACS on STN	
1.1	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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ΡI		A1 HU, MD, PL		WO 1997-RU274 US	19970826
L4	ANSWER 41 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Fixative vinyl a			S	
	PATENT NO.		DATE		
DT				HC 1007 057054	
PI	110 6077770	7.	19981103	US 1997-857954 US 1998-34574	19980304
	WO 9851266	A2	19981119	US 1998-34574 WO 1998-US5318	19980318
	WO 9851266	A3	19990218		
				BG, BR, BY, CA, CH, CN,	
	DK, EE,	ES, FI, GB	, GE, GH,	GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK,	JP, KE, KG,
	KP, KR, NO NZ	PI, PT RO	, ык, ыз, RII SD	SE, SG, SI, SK, SL, TJ,	TM. TR. TT.
				AZ, BY, KG, KZ, MD, RU,	
	RW: GH, GM,	KE, LS, MW	, SD, SZ,	UG, ZW, AT, BE, CH, DE,	DK, ES, FI,
				NL, PT, SE, BF, BJ, CF,	CG, CI, CM,
		ML, MR, NE		TG AU 1998-68659	19990210
	AU 9868659	ΑI	12201708	MO 1330-00033	19980318
L4	ANSWER 42 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Selective etchin	g of diele	ctrics us	ing fluorohydrocarbon gas	3,
	NH3-generating g	as, and ca	rbon-oxyq	en qas	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI		- A			

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A 19981201 US 1996-639388
A2 19980213 JP 1997-112887
A2 19980224 JP 1997 177
                            19980224 JP 1997-147995
19971217 EP 1997-304035
    JP 10056001
                                                            19970605
                      A2 19971217
A3 19990825
    EP 813233
                                                            19970610
    EP 813233
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
    ANSWER 43 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Spray formulation for testing of smoke detectors
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
                                                           DATE
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                            19980728 US 1996-713058
                                                            19960912
                       Α
ΡI
    US 5785891
    ANSWER 44 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Coolant agent composition
                                      APPLICATION NO.
                                                           DATE
    PATENT NO. KIND
                            DATE
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                            19971210 RU 1996-104188
                                                            19960301
PΙ
    RU 2098445
                      C1
    ANSWER 45 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
1.4
    Method and apparatus for fluorine-assisted stripping and residue removal
    PATENT NO. KIND DATE APPLICATION NO. DATE
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                                      _____
    ______
                      A1 19980402 WO 1997-US16886
                                                           19970924
    WO 9814036
PΙ
        W: JP, KR, US
        RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                      A1 19981007 EP 1997-944360
                                                           19970924
       R: DE, FR, GB, IT, NL
                            20000208 JP 1998-515793
20000704 US 1997-936548
                                                           19970924
    JP 2000501573 T2
                                                           19970924
    US 6082374
                       Α
L4
    ANSWER 46 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Palladium-assisted electrodehalogenation of 1,1,2-trichloro-1,2,2-
    trifluoroethane on lead cathodes combined with hydrogen diffusion anodes
    ANSWER 47 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Process for the reduction of chlorofluorocarbons and production of
ΤI
    derivatives thereof in an electrolytic cell, cell for carrying out said
    reduction and process for removing the byproducts formed within the cell
    PATENT NO. KIND DATE APPLICATION NO. DATE
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                      A1 19970710 WO 1996-ES248
                                                           19961226
    WO 9724162
PΤ
        W: CA, US
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    ES 2103207 A1 19970816 ES 1995-2533
                                                            19951228
    ES 2103207
                      B1
                            19980401
    EP 819448
EP 819448
                            19980121 EP 1996-941667
                                                           19961226
                      A1
                           20000517
                      B1
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
                       E
                            20000615
                                       AT 1996-941667
                                                            19961226
    AT 192939
                      Т3
                            20001016
                                       ES 1996-941667
                                                           19961226
    ES 2148819
                            20000530
                                     US 1997-913389
                                                           19971104
    US 6068756
                       Α
    ANSWER 48 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Large scale fluorine doped textured transparent conducting SnO2 films
TI
    deposited by atmospheric pressure chemical vapor deposition
    ANSWER 49 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Smell-added refrigerant compositions for leakage detection
TТ
    PATENT NO. KIND DATE APPLICATION NO.
                                                           DATE
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                      A2
                            19960924 JP 1995-51647
                                                           19950313
PΙ
    JP 08245952
    ANSWER 50 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Evaluation of critical parameters of halohydrocarbons and its quality
TI
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US 5843847 JP 10041274

codes

19960429

19970430

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ANSWER 51 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
    Single-phase aerosol antiperspirant composition
    PATENT NO. KIND DATE APPLICATION NO. DATE
    WO 9618378 A2 19960620 WO 1995-US16286 19951214
PΙ
        W: AU, BR, CA, CH, CN, DE, ES, FI, GB, JP, KR, NO, NZ, PL, PT, RO,
           RU, SE, UA, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                      A1 19960703 AU 1996-49618
                                                           19951214
    AU 9649618
    ANSWER 52 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Ab initio studies of fluorinated ethanes: electronic and energetic
TI
    properties and reactions with hydroxyl radicals
    ANSWER 53 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Dehydrofluorination, fluorination, and decomposition of fluorohydrocarbons
TT
    with phosphate catalysts
                KIND
                            DATE APPLICATION NO.
                                                            DATE
    PATENT NO.
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                            _____
                                       ______
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                     A2
    JP 08104656
                            19960423 JP 1994-243024
                                                            19941006
PΙ
    ANSWER 54 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation of a substrate having a fluoride-doped conductive coating
TT
    PATENT NO. KIND DATE APPLICATION NO. DATE
    US 5496583 A 19960305 US 1994-297400 19940829
WO 9606958 A1 19960307 WO 1995-US10854 19950828
ΡI
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI,
           GB, GE, HU, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD,
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           TM, TT
        RW: KE, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT,
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           SN, TD, TG
                                       AU 1995-34959
                       A1
                            19960322
                                                            19950828
    AU 9534959
    ANSWER 55 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Four-component aerosol compositions
ΤI
                                      APPLICATION NO. DATE
    PATENT NO. KIND DATE
                      A1 19960111 WO 1994-US7426 19940630
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    WO 9600564
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                            19960125
                                     AU 1994-73206
    AU 9473206
                      A1
    ANSWER 56 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Aerosol detergent compositions with low toxicity for cleaning automotive
    brakes
                            DATE APPLICATION NO.
    PATENT NO.
                     KIND
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                                      JP 1994-126602
ΡI
    JP 07331290
                      A2
                            19951219
                                                           19940608
    ANSWER 57 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Infrared photochemical properties of sensitized SO2-O2 mixtures
    ANSWER 58 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
TI
    Energy-saving binary refrigerant mixtures without ozone layer depletion
    effect
    PATENT NO.
                     KIND DATE
                                   APPLICATION NO.
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                           19950125
                                      CN 1993-109083
PΙ
    CN 1097792
                      Α
                                                           19930721
    ANSWER 59 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Hair aerosol compositions containing polymers and dimethylether
    PATENT NO. KIND DATE APPLICATION NO. DATE
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ΡI	EP 663203 EP 663203	A1 1995071 B1 2001091		19941213
			3, IT, LI, NL, SE 21 FR 1994-367	19940114
				10041212
	AT 205698 CA 2138481	E 2001101 AA 1995071	L5 CA 1994-2138481	19941213 19941219
	CA 2138481 HU 71747	C 2002062 A2 1996012	29 HU 1994-3827	19941229
	HU 218577	B 2000102 B1 2000013		19941229
	PL 177758			
	KR 166391	B1 1999011		19941230
	BR 9500140	A 1995101		19950110
	CN 1113141	A 1995121		19950113
	CN 1070358	B 2001090		
	JP 08040847	A2 1996021		19950113
	JP 2834417	B2 1998120)9	
	RU 2124351	C1 1999011	LO RU 1995-100766	19950113
	US 6113923	A 2000090	05 US 1995-372395	19950113
L4	ANSWER 60 OF 214	CAPLUS COPYRIGH	HT 2006 ACS on STN	
TI			facture of rigid foams	
	PATENT NO.	KIND DATE	APPLICATION NO.	DATE
DT	US 5391584	A 1995022		19930308
ΡI				19920313
	ZA 9201888			
	ZA 9201895	A 1992123		19920313
	CN 1067435	A 1992123		19920327
	KR 227876	B1 1999110		19920327
	US 5238970	A 1993082		19921110
	US 5240965	A 1993083		19921110
	US 5356556	A 1994101	18 US 1993-61007	19930514
	US 5368769	A 1994112	29 US 1993-67789	19930527
	CN 1133854	A 1996102	23 CN 1995-119832	19951114
	CN 1048995	В 2000020)2	
L4	ANSWER 61 OF 214	CAPLUS COPYRIGH	HT 2006 ACS on STN	
TI			luoroethane-based refrige	rating agents
	PATENT NO.	KIND DATE	APPLICATION NO.	DATE
ΡI	JP 07027431	A2 1995012	27 JP 1993-176804	19930716
	01 07017001			
L4	ANSWER 62 OF 214	CAPLUS COPYRIGH	HT 2006 ACS on STN	
TI			ate with a gas containing	excited halogen
	to remove residues		.cc "1011 a gab conculting	
			ADDITCATION NO	DATE
	FAIBNI NO.	KIND DATE	APPLICATION NO.	
ΡI			26 WO 1994-US7751	
FI	W: JP, KR, US		10 WO 1994 007731	13340712
			ם כם כם דה דה דון אכ	NI. DT SE
	RW: AI, BE, CH	, DE, DK, ES, FF	R, GB, GR, IE, IT, LU, MC 08 EP 1994-922123	, NU, PI, SE
	EP 710161	A1 1996050	J8 EP 1994-922123	19940712
	R: DE	mo 1000001	TD 1004 F046F0	10040712
	JP 09502646	12 1997031	L8 JP 1994-504652	19940/12
L4	ANSWER 63 OF 214			
TI		ctrically conduc	ctive, soluble pyrrole-3-	carboxylic acid
	ester polymers			
	PATENT NO.	KIND DATE	APPLICATION NO.	DATE
ΡI	JP 06206986	A2 1994072	26 JP 1992-180695	19920708
	JP 3024867	B2 2000032	27	
L4	ANSWER 64 OF 214			
TI	Testing agents for	smoke detectors	and their manufacture	
			APPLICATION NO.	DATE
ΡI	CN 1084274	A 1994032	23 CN 1993-119728	19931104
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L4	ANSWER 65 OF 214	CAPLUS COPYRIGE	HT 2006 ACS on STN	

TI	Substance separati gas-mixture flows			a pulsed IR laser radia	ation on
L4 TI	ΡΔΤΈΝΤ ΝΟ	rmoplas	tic polyester	r foams by extrusion APPLICATION NO.	DATE
ΡI	JP 06145404 JP 2801483	A2 B2	19940524 19980921	JP 1992-317764	19921102
L4 TI	dimensional stabil PATENT NO.	em for p ity KIND	preparation o	of rigid polyurethane for APPLICATION NO.	DATE
PI	DE 4303887	A1	19940421	DE 1993-4303887	19930210
L4 TI	ANSWER 68 OF 214 Gaseous doping of PATENT NO.	tungste	n oxide	APPLICATION NO.	DATE
ΡI	US 5324537	A	19940628	US 1993-86796	19930706
L4 TI	ANSWER 69 OF 214 Hydrofluorocarbon static magnetron			006 ACS on STN licon dioxide etch in an	ı axisymmetric
L4 TI	ANSWER 70 OF 214 Manufacture of sem PATENT NO.	iconduct	tor devices	APPLICATION NO.	DATE
ΡI	JP 06029263	A2	19940204	JP 1992-179993	19920707
L4 TI	ANSWER 71 OF 214 Manufacture of sem PATENT NO.	niconduct KIND	tor device by DATE		DATE
ΡI				JP 1992-174114	
L4 TI	ANSWER 72 OF 214 Manufacture of fle PATENT NO.	xible po	olyurethane	006 ACS on STN foams having low density APPLICATION NO.	DATE
PI	JP 05320300			JP 1992-134451	
L4 TI	ANSWER 73 OF 214 Antiperspirant aer PATENT NO.	cosol cor	mposition wit	006 ACS on STN th high solid content APPLICATION NO.	DATE
PI	CA 2093781 AU 9336751 AU 671104 EP 570085	AA A1 B2 A2	19931017 19931021 19960815 19931118	CA 1993-2093781 AU 1993-36751	19930408 19930406
	EP 570085 R: AT, BE, CH	A3 [, DE, DI	19940309 K, ES, FR, G	B, IE, IT, LI, LU, NL, S	SE 19930415
	ZA 9302658 US 5605682 US 5605682	A A B1	19941015 19970225 19990223	BR 1993-1551 ZA 1993-2658 US 1994-238195	19930415 19940504
L4 TI	ANSWER 74 OF 214 Dependence of the	CAPLUS gas-chro	COPYRIGHT 20 omatographic	006 ACS on STN retention parameters fo physicochemical charact	
L4 TI	ANSWER 75 OF 214 Stabilized polyoxy PATENT NO.	alkylene KIND	e glycols DATE	OO6 ACS on STN APPLICATION NO.	DATE
PI				WO 1992-US2148	

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W: AU, BB, BG, BR, CA, CS, FI, HU, JP, KP, KR, LK, MG, MN, MW, NO,
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   RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, DE, DK, ES, FR, GA, GB, GN,
      GR, IT, LU, MC, ML, MR, NL, SE, SN, TD, TG
                     19921102
                            AU 1992-17754
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AU 9217754
ANSWER 76 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
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PATENT NO.
               KIND
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                     19930514
                             JP 1991-281038
JP 05117646
                A2
                                                 19911028
ANSWER 77 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
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PATENT NO.
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                             JP 1991-171032
                A2
                     19930126
                                                 19910711
JP 05017743
ANSWER 78 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
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PATENT NO.
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                             JP 1991-171035
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JP 05017746
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ANSWER 79 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO.
PATENT NO.
               KIND DATE
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                             JP 1991-172368
JP 05017748
               A2
                     19930126
                                                19910712
ANSWER 80 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO.
PATENT NO.
               KIND DATE
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JP 05017751
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                     19930126
                             JP 1991-172371
                                                19910712
ANSWER 81 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO.
PATENT NO.
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                             JP 1991-172375 19910712
JP 05017755
               A2 19930126
ANSWER 82 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
PATENT NO.
              KIND DATE
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                                                DATE
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                              -----
                             JP 1991-172378
JP 05017758
               A2 19930126
                                                19910712
ANSWER 83 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Prediction of refrigerant thermodynamic properties by equations of state:
vapor liquid equilibrium behavior of binary mixtures
ANSWER 84 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Crosslinked polyolefin foaming compositions
PATENT NO. KIND DATE APPLICATION NO.
                                               DATE
                              -----
               A2 19920602
JP 04159339
                             JP 1990-283331
                                                19901023
ANSWER 85 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Performance-oriented packaging standards; changes to classification,
hazard communication, packaging and handling requirements based on UN
standards and agency initiative
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L4 ANSWER 86 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Manufacture of expandable vinylidene chloride resin particles
PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 03223346 A2 19911002 JP 1990-17733 19900130

	aroarnanosron	the hydr	coxyl radical		se reaction o
54 CI				2006 ACS on STN dings for thermal insu	ılators of
	refrigerators PATENT NO.			APPLICATION NO.	
Ί	JP 03225182			JP 1990-17732	
.4 'I	ANSWER 89 OF 214 Preparation of th				
1	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
I	JP 03137139		19910611	JP 1989-276342	19891023
4	ANSWER 90 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
Ι	Working fluids PATENT NO.		DATE		
Ξ.	JP 03220285 JP 2532736	A2	19910927	JP 1990-242131	
<u> </u>		ering sa	fety data of	2006 ACS on STN E the material pair RI nventional refrigerant	
1	ANSWER 92 OF 214 Working fluids	CAPLUS	COPYRIGHT 2	2006 ACS on STN	•
	warking illias		D ልጥ ድ	ADDITORMIONI NO	
	PATENT NO.			APPLICATION NO.	DATE
Ι	PATENT NO	 A2	 19910724	 JР 1989-311149	19891130
Ι	PATENT NO	 A2	 19910724		19891130
I I 4	PATENT NO. JP 03170583 US 5433879 ANSWER 93 OF 214	A2 A	19910724 19950718	JP 1989-311149 US 1993-125146	19891130
	PATENT NO. JP 03170583 US 5433879 ANSWER 93 OF 214 Working fluids PATENT NO.	A2 A CAPLUS KIND	19910724 19950718 COPYRIGHT 2	JP 1989-311149 US 1993-125146 2006 ACS on STN APPLICATION NO.	19891130 19930923 DATE
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[[[PATENT NO. JP 03170583 US 5433879 ANSWER 93 OF 214 Working fluids PATENT NO. JP 03168271 ANSWER 94 OF 214	A2 A CAPLUS KIND	19910724 19950718 COPYRIGHT 2 DATE 19910722	JP 1989-311149 US 1993-125146 2006 ACS on STN APPLICATION NO. JP 1989-309652	19891130 19930923 DATE
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I I	PATENT NO. JP 03170583 US 5433879 ANSWER 93 OF 214 Working fluids PATENT NO. JP 03168271 ANSWER 94 OF 214 Working fluids	A2 A CAPLUS KIND A2 CAPLUS	19910724 19950718 COPYRIGHT 2 DATE 19910722 COPYRIGHT 2 DATE	JP 1989-311149 US 1993-125146 2006 ACS on STN APPLICATION NO. JP 1989-309652	DATE 19891129

ΡI	JP 03170583 US 5433879	A2 A	19910724 19950718		19891130 19930923
L4 TI	ANSWER 93 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03168271			JP 1989-30 9652	19891129
L4 TI	ANSWER 94 OF 214 Working fluids		COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE		DATE
PI	JP 03170593			JP 1989-311164	19891130
L4 TI	ANSWER 95 OF 214 Working fluids			2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	
PI	JP 03170592 US 5433879		19910724	JP 1989-311163	
L4 TI	ANSWER 96 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03170590 JP 2580349	A2		JP 1989-311160	19891130
	US 5304319	A	19940419	US 1992-839700	19920224
L4 TI	ANSWER 97 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03170589				
L4	ANSWER 98 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	

ті	Working fluids PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03168261	A2		JP 1989-309640	
L4	ANSWER 99 OF 214	CAPLUS	COPYRIGHT 20	006 ACS on STN	
TI	Working fluids PATENT NO.			APPLICATION NO.	
PI	JP 03168287			JP 1989-309669	
L4	ANSWER 100 OF 214 Working fluids	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI		KIND		APPLICATION NO.	DATE
PI	JP 03168290				19891129
L4 TI	layer depletion	paration	of urethane	foaming solutions witho	
	PATENT NO.			APPLICATION NO.	
PI		A2		JP 1989-289729	19891106
L4	ANSWER 102 OF 214				
TI	Apparatus for man	KIND	of foaming u	rethane solutions APPLICATION NO.	DATE
PI	JP 03150108 JP 2706991	A2	19910626	JP 1989-289728	19891106
L4 TI	ANSWER 103 OF 214 Semiempirical cal- silicon inner core	culation	of ESCA shift	ts in oxygen, nitrogen,	fluorine and
L4	ANSWER 104 OF 214				
TI	Aerosol composition PATENT NO.	KIND	DATE	APPLICATION NO.	
PI	EP 423695	A2	19910424	EP 1990-119769	19901015
	EP 423695	A3	19911002		
				B, GR, IT, LI, NL, SE	
	AU 9064634	A1	19910426	AU 1990-64634	19901015
	NO 9004492 CA 2027952	A	19910422	NO 1990-4492	19901017
	JP 03255023	AA 2	19910420	NO 1990-4492 CA 1990-2027952 JP 1990-281690	19901018 19901019
	US 5378451	A	19950103	US 1993-126747	19930927
L4	ANSWER 105 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI	Etching of semicon	nductor v	with fluoride	and hydrocarbon gas	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 03083335	Δ2	19910409	TP 1989-218530	19890828
	EP 497023	A1	19920805		19910131
	R: DE, FR, G US 5110408	B A		US 1991-658254	
L4 TI	PATENT NO.	gid polyt KIND	rethane foam DATE	ns with low thermal cond APPLICATION NO.	DATE
PI	EP 421269 EP 421269 EP 421269 EP 421269	B1	19910904	EP 1990-118532	19900927
	R: AT, BE, C	H, DE, DH		B, IT, LI, NL, SE	
	DE 3933335 DE 3933335	A1 C2		DE 1989-3933335	19891006

	US 5096933 US 5096933	A B1	19920317 19960326	US	1990-577174	19900904
	CA 2024714	AA	19910407	CA	1990-2024714	19900906
	CA 2024714	С	19980623			
	AT 132882	E	19960115		1990-118532	
	ES 2081887	T3	19960316		1990-118532	
	JP 03152160	A2	19910628	JP	1990-266573	19901005
	JP 3216646 KR 173981	B2 B1	20011009 19990401	מע	1990-15963	19901006
	KR 1/3981	вт	19990401	KK	1990-15963	19901006
L4 TI	ANSWER 107 OF 214 Working fluid	CAPLUS	COPYRIGHT :	2006	ACS on STN	
	PATENT NO.	KIND	DATE		PLICATION NO.	DATE
ΡI	EP 430170		19910605		1990-122653	
FI	EP 430170	B1	19940803		2330 222030	
•	R: DE, FR, GB		10000			
	JP 03170584	A2	19910724	JР	1989-311153	19891130
	JP 2532695	B2	19960911			
	JP 03170587		19910724	JР	1989-311156	19891130
	JP 2532696	B2	19960911			
L4 TI	ANSWER 108 OF 214 Working fluid		COPYRIGHT :	2006	ACS on STN	
	PATENT NO.	KIND	DATE	API	PLICATION NO.	DATE
PΙ	EP 430171		19910605	EP	1990-122654	19901127
	EP 430171	B1	19931006			
	R: DE, FR, GB					
	JP 03172384	A2	19910725	JP	1989-311166	19891130
	JP 2532697	B2	19960911			
		A2	19910725	JP	1989-311168	19891130
	JP 2548412	B2	19961030			
T A	ANGWED 100 OF 214	CADITIC	CODVETCUT 1	2006	ACS OR STIN	
L4	ANSWER 109 OF 214					ירו די)
L4 TI	ANSWER 109 OF 214 Catalytic hydrodec					ClF2)
TI	Catalytic hydrodec	hlorinat	ion of freom	n 113	3, (CFC 113, CCl2FC	ClF2)
TI L4	Catalytic hydrodec	hlorinat CAPLUS	ion of freom	n 113 2006	3, (CFC 113, CCl2FC ACS on STN	
TI	Catalytic hydrodec	hlorinat CAPLUS	ion of freomotion of copyright and chemically	n 113 2006 enha	3, (CFC 113, CCl2FC ACS on STN anced sputtering of	solids
TI L4	Catalytic hydrodec ANSWER 110 OF 214 Production of ion	hlorinat CAPLUS beams by KIND	ion of freomotion of copyright and chemically DATE	n 113 2006 enha API	3, (CFC 113, CCl2FC ACS on STN	solids DATE
TI L4	ANSWER 110 OF 214 Production of ion PATENT NO.	hlorinat CAPLUS beams by KIND	ion of freomotion COPYRIGHT 2 chemically DATE	n 113 2006 enha API	ACS on STN ACS on STN anced sputtering of PLICATION NO.	solids DATE
TI L4 TI	ANSWER 110 OF 214 Production of ion PATENT NO	hlorinat CAPLUS beams by KIND A1	ion of freomotion COPYRIGHT 2 chemically DATE	n 113 2006 enha API	ACS on STN anced sputtering of PLICATION NO.	solids DATE
TI L4 TI	ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303	hlorinat CAPLUS beams by KIND A1	COPYRIGHT 2 chemically DATE 19900907	n 113 2006 enha API	ACS on STN anced sputtering of PLICATION NO.	solids DATE
TI L4 TI	ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP	hlorinat CAPLUS beams by KIND A1 A3	COPYRIGHT 2 chemically DATE 19900907 19901018	n 113 2006 enha API WO	ACS on STN ACS on STN ACCLATION NO. 1990-US677	solids DATE
TI L4 TI	ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP	CAPLUS beams by KIND A1 A3	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, G	n 113 2006 enha APE WO	ACS on STN anced sputtering of PLICATION NO.	solids DATE 19900206
TI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746	CAPLUS beams by KIND A1 A3 , DE, DK A	COPYRIGHT : chemically DATE	n 113 2006 enha API WO WO	ACS on STN ACS on STN ACS on STN ACS of SPLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504	solids DATE 19900206
TI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GH 19920218	n 113 2006 enha API WO WO	ACS on STN	solids DATE 19900206
TI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating co	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GH 19920218 COPYRIGHT 2 mprising lice	n 113 2006 enha APE WO B, IT US 2006 ght m	ACS on STN	solids DATE 19900206
TI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WI JP, KP RWI AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND	COPYRIGHT : Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT : mprising lig	2006 enha API WO B, IT US 2006 ght m	ACS on STN Anced sputtering of PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN Metal fluorides PLICATION NO.	solids DATE 19900206
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WO: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND	COPYRIGHT Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT Cop	n 113 2006 enha API WO B, IT US 2006 ght n	ACS on STN Anced sputtering of PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN Metal fluorides PLICATION NO.	DATE DATE 19900206
TI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WO 9010303 WO JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205	n 113 2006 enha API WO B, IT US 2006 ght n	ACS on STN Anced sputtering of PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN Metal fluorides PLICATION NO.	solids DATE 19900206
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205	n 113 2006 enha API WO B, IT US 2006 ght n	ACS on STN Anced sputtering of PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN Metal fluorides PLICATION NO.	DATE 19890214 DATE DATE
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WO JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 EP 400796 FO DE FR GR	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1	COPYRIGHT Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT Cop	n 113 2006 enha API WO B, IT US 2006 ght n APE EP	ACS on STN	DATE 19890214 DATE 19900417
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WO JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 EP 400796 FO DE FR GR	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1	COPYRIGHT Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT Cop	n 113 2006 enha API WO B, IT US 2006 ght n APE EP	ACS on STN	DATE 19890214 DATE 19900417
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WO JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 EP 400796 FO DE FR GR	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1	COPYRIGHT Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT Cop	n 113 2006 enha API WO B, IT US 2006 ght n APE EP	ACS on STN ENCED 113, CC12FC ACS on STN ENCED SPUTTERING OF PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN ENCED 1980-311504 ACS ON STN ENCED 1990-304073	DATE 19900206 19890214 DATE 19900417
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1	COPYRIGHT Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT Cop	n 113 2006 enha API WO B, IT US 2006 ght n APE EP	ACS on STN ENCED 113, CC12FC ACS on STN ENCED SPUTTERING OF PLICATION NO. 1990-US677 T, LU, NL, SE 1989-311504 ACS on STN ENCED 1980-311504 ACS ON STN ENCED 1990-304073	DATE 19890214 DATE 19900417
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO WO 9010303 WO 9010303 WI JP, KP RWI AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A	COPYRIGHT : chemically DATE	n 113 2006 enha API WO B, IT US 2006 ght m API EP CA JP US	ACS on STN	DATE 19900206 19890214 DATE 19900417
TI L4 TI PI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 WO 9010303 WI JP, KP RWI AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 RI DE, FR, GB CA 2015802 JP 03017601 US 5208101 ANSWER 112 OF 214	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS	COPYRIGHT : Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT : mprising lig DATE 19901205 19940316 19901130 19910125 19930504 COPYRIGHT :	2006 enha API US 2006 EP CA JP US 2006	ACS on STN	DATE 19900206 19890214 DATE 19900417
TI L4 TI PI L4 TI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO WO 9010303 WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS me-retare	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205 19940316 19901130 19910125 19930504 COPYRIGHT 2 dant styrene	2006 enha API WO B, IT 2006 ght m APE EP CA JP US 2006 eres	ACS on STN Include the state of the state o	DATE 19900206 19890214 DATE 19900417 19900501 19900529 19910701
TI L4 TI PI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 R: DE, FR, GB CA 2015802 JP 03017601 US 5208101 ANSWER 112 OF 214 Manufacture of flat PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS me-retare KIND	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205 19940316 19901130 19910125 19930504 COPYRIGHT 2 dant styrene	2006 enha API WO B, IT 2006 ght m API EP CA JP US 2006 e res API	ACS on STN	DATE 19900206 19890214 DATE 19900417
TI L4 TI PI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 R: DE, FR, GB CA 2015802 JP 03017601 US 5208101 ANSWER 112 OF 214 Manufacture of flat PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS me-retare KIND	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205 19940316 19901130 19910125 19930504 COPYRIGHT 2 dant styrene DATE	2006 enha API WO B, IT 2006 ght m APE EP CA JP US 2006 e res APE	ACS on STN In LU, NL, SE 1990-US677 C, LU, NL, SE 1989-311504 ACS on STN metal fluorides PLICATION NO. 1990-2015802 1990-304073 ACS on STN 1990-139560 1991-723992 ACS on STN sin laminar foams PLICATION NO.	DATE 19900206 19890214 DATE 19900417 19900501 19900529 19910701 DATE
TI L4 TI PI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 R: DE, FR, GB CA 2015802 JP 03017601 US 5208101 ANSWER 112 OF 214 Manufacture of flat PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS me-retare KIND A2	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205 19940316 1990130 19910125 19930504 COPYRIGHT 2 dant styrene DATE 19900510	2006 enha API WO B, IT 2006 ght m APE EP CA JP US 2006 e res APE	ACS on STN In LU, NL, SE 1990-US677 C, LU, NL, SE 1989-311504 ACS on STN metal fluorides PLICATION NO. 1990-2015802 1990-304073 ACS on STN 1990-139560 1991-723992 ACS on STN sin laminar foams PLICATION NO.	DATE 19900206 19890214 DATE 19900417 19900501 19900529 19910701 DATE
TI L4 TI PI L4 TI PI	Catalytic hydrodec ANSWER 110 OF 214 Production of ion PATENT NO. WO 9010303 W: JP, KP RW: AT, BE, CH US 5089746 ANSWER 111 OF 214 Anti-reflective co PATENT NO. EP 400796 EP 400796 R: DE, FR, GB CA 2015802 JP 03017601 US 5208101 ANSWER 112 OF 214 Manufacture of flat PATENT NO.	CAPLUS beams by KIND A1 A3 , DE, DK A CAPLUS ating con KIND A1 B1 AA A2 A CAPLUS me-retare KIND A2	COPYRIGHT 2 Chemically DATE 19900907 19901018 , ES, FR, GR 19920218 COPYRIGHT 2 mprising lig DATE 19901205 19940316 1990130 19910125 19930504 COPYRIGHT 2 dant styrene DATE 19900510	2006 enha API WO B, IT 2006 ght m APE EP CA JP US 2006 e res APE	ACS on STN In LU, NL, SE 1990-US677 C, LU, NL, SE 1989-311504 ACS on STN metal fluorides PLICATION NO. 1990-2015802 1990-304073 ACS on STN 1990-139560 1991-723992 ACS on STN sin laminar foams PLICATION NO.	DATE 19900206 19890214 DATE 19900417 19900501 19900529 19910701 DATE

L4 ANSWER 113 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Laser induced nonstationary processes in gaseous mixtures through porous media

L4	ANSWER 114 OF 214	CAPLUS	COPYRIGHT :	2006 ACS on STN	
TI	Combining a blowing polyurethane foam PATENT NO.		ure DATE	st one liquid reaction APPLICATION NO.	DATE
ΡI	DE 3819630	A1 A2	19891214	DE 1988-3819630 EP 1989-109610	19880609
	EP 345580 R: AT, BE, CH JP 02039921	A3 I, DE, ES A2	, FR, GB, I	Г, LI, NL, SE JP 1989-143203	
L4 TI	ANSWER 115 OF 214 Heat pumps with fl PATENT NO.	uorocarb KIND	on working : DATE	fluids APPLICATION NO.	DATE
ΡI	JP 01200153			JP 1988-25011	
L4 TI		ing deac	tivated Gro	2006 ACS on STN up VIII element-zeolite	e catalysts for
	aromatic compound PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 316727 EP 316727 R: BE, CH, DE	A1 B1	19890524 19920122	EP 1988-118621	
	US 4937215	A A1	19900626 19930518	US 1988-256697 CA 1988-580661 JP 1988-280348	19881019
т 4	ANSWER 117 OF 214				13001100
L4 TI	Pyrolytically coat PATENT NO.			ts manufacture	DATE
ΡI	DE 3823089 GB 2206878		19890119 19890118 19910717	DE 1988-3823089	19880707 19870711
	ES 2006972	A6	19890516	ES 1988-1782	19880608
		A4 A1 B1	198901016	BE 1988-683 FR 1988-8210	19880615 19880616
	FR 2617833 AT 8801725	A	19920417 19940615	AT 1988-1725	19880704
	NL 8801713	A	19890201	NL 1988-1713	19880707
	CH 675416 SE 8802578	A A	19900928 19890112	CH 1988-2595 SE 1988-2578	19880707
	SE 465921	R R	19911118	SE 1900-2576	19880708
	SE 465921 SE 465921 JP 01033033	Ċ	19920312		
	JP 01033033	A2	19890202	JP 1988-170751	19880708
L4 TI	ANSWER 118 OF 214 Multilayer heat in				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI				JP 1986-297088	
L4 TI		ting ele		2006 ACS on STN l sensors from biofouli	ing in an
	aquatic environmen PATENT NO.	KIND	DATE	APPLICATION NO.	
PI	US 4763537	A	19880816	US 1986-941774	
L4 TI				2006 ACS on STN ows through capillaries	3
L4 TI	ANSWER 121 OF 214 Aerosol waterproof	sunscre	en compositi	ions	DATE
	PATENT NO.			APPLICATION NO.	
PI	US 4686099	Α		US 1985-807488	

	GB 2202740 GB 2202740	A1 B2	19881005 19901212	GB 1987-7617	19870331
L4 TI	ANSWER 122 OF 214 Improvement of the			2006 ACS on STN ance of bottles by surfa	ce treatment
L4 TI	ANSWER 123 OF 214 Manufacture of hol PATENT NO.	low fibe	rs	2006 ACS on STN APPLICATION NO.	DATE
ΡI	JP 62117813	A2	19870529	JP 1985-255018	19851115
L4 TI	ANSWER 124 OF 214 Laser action on ga			2006 ACS on STN rough metal capillaries	
L4 TI	ANSWER 125 OF 214 Silica film etchin	g		2006 ACS on STN	·
	PATENT NO.	KIND		APPLICATION NO.	DATE
PI	JP 61251138			JP 1985-93024	19850430
L4 TI	ANSWER 126 OF 214 Effect of laser rac capillaries in a t	diation (on the pass	sage of resonance molecu	les through
L4	ANSWER 127 OF 214 Semiconductor devi		COPYRIGHT	2006 ACS on STN	
TI	PATENT NO.	KIND			
PI	JP 60143633 JP 61004179	A2 B4	19850729 19860207	JP 1984-250543	19841129
L4 TI	ANSWER 128 OF 214 Nonflammable aerose PATENT NO.	ol prope KIND	llant micro	pemulsion system APPLICATION NO.	DATE
ΡΙ	US 4536323 CA 1205349 AU 574715 AU 8433083 US 4655959	A A1 B2 A1	19850820 19860603 19880714 19860327	US 1983-508643 CA 1984-457246 AU 1984-33083 US 1985-749962	
L4 TI	ANSWER 129 OF 214 Gas and method for PATENT NO.	selecti	ve etching	of silicon nitride	DATE
·PI	DE 3420347 DE 3420347 JP 59222933 JP 60115232 NL 8401774 US 4529476	A1 C2 A2 A2 A	19841206 19870820 19841214 19850621 19850102 19850716	APPLICATION NO. DE 1984-3420347 JP 1983-95651 JP 1983-222072 NL 1984-1774 US 1984-616114	19840530 19830601 19831128 19840601 19840601
L4 TI	ANSWER 130 OF 214 Limit of thermal ig			2006 ACS on STN -initiated unbranched cl	hain reaction
L4 TI	ANSWER 131 OF 214 Determination of pa molecules			2006 ACS on STN steraction potential of p	polar
L4 TI	compound	ım gas o	ils with ca	talyst and an added orga	
	PATENT NO.	KIND	DATE	APPLICATION NO.	
PI				US 1981-301754 JP 1983-77342	

ANSWER 133 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

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\mathtt{TI}	Foamed body of a	vinyl chlo	resin composition			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE	
						
ΡI	GB 2110216	A1	19830615	GB 1982-32528	19821115	
	JP 58084832	A2	19830521	JP 1981-183349	19811116	
	JP 62017613	B4	19870418			
	JP 58087135	A2	19830524	JP 1981-185968	19811119	
	JP 02030341	B4	19900705			

- L4 ANSWER 134 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of vinyl chloride, trifluorochloroethylene, difluoroethane, hexafluoropropylene, and hexafluoropropylene oxide in water
- L4 ANSWER 135 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Viscosity of difluoroethane
- L4 ANSWER 136 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Specification and usage requirements for 3AL seamless, aluminum cylinders
- L4 ANSWER 137 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Fluorination of catalysts

	riudiinacion di c	acaryscs			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PΙ	GB 2024642	Α	19800116	GB 1979-23338	19790704
	GB 2024642	B2	19820818		
	FR 2430263	A1	19800201	FR 1978-20182	19780706
	FR 2430263	B1	19810102		
	CA 1137062	A1	19821207	CA 1979-3263 92	19790426
	NL 7905206	Α	19800108	NL 1979-5206	19790704
	DE 2927052	A1	19800117	DE 1979-2 927052	19790704
	JP 55011097	A2	19800125	JP 1979-84050	19790704
	JP 62052623	B4	19871106		

- L4 ANSWER 138 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solvent effects on the distribution coefficients. III. The solubility of some lower fluoro- and chlorohydrocarbons in organic solvents
- L4 ANSWER 139 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of gas-kinetic diameters of molecules of difluoroethane and fluoro-substituted derivatives of ethylene
- L4 ANSWER 140 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of the gas-kinetic diameters of molecules of difluoroethane and fluorine-substituted derivatives of ethylene
- L4 ANSWER 141 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 142 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Study of the thermal conductivity of toluene and some difluoroethanes at high pressures
- L4 ANSWER 143 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VIII. Respiration and circulation in primates
- L4 ANSWER 144 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 145 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VI. Influence of cardiac and pulmonary vascular lesions in the rat
- L4 ANSWER 146 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Cardiopulmonary toxicity of propellants for aerosols

- L4 ANSWER 147 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of chlorine, hydrogen chloride, difluoro- and difluorochloroethanes in chloroorganic solvents
- L4 ANSWER 148 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants on the respiratory and circulatory systems. III. Influence of bronchopulmonary lesion on cardiopulmonary toxicity in the mouse
- L4 ANSWER 149 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. IV. Cardiotoxicity in the monkey
- L4 ANSWER 150 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Identification of absorption lines in gases used to modulate the carbon dioxide laser
- L4 ANSWER 151 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Thermal energy electron attachment rate constants for some polyatomic molecules
- L4 ANSWER 152 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Regeneration of hydrocracking catalysts

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE			
ΡI	DE 2249892	A1	19730419	DE 1972-2249892	19721011			
	US 3725244	Α	19730403	US 1971-188408	19711013			

- L4 ANSWER 153 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hydrocracking catalyst activation treatment

	PATENT NO.	KIND DATE		APPLICATION NO.	DATE		
ΡI	US 3673108	A	19720627	US 1969-889681	19691231		

- L4 ANSWER 154 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Homopolymers and copolymers of vinylidene fluoride

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
FR 1570233		19690606	FR	
DE 1770672			DE	
GB 1188889			GB	
US 3616371		19710000	US	
	PATENT NO. 	FR 1570233 DE 1770672 GB 1188889	FR 1570233 19690606 DE 1770672 GB 1188889	FR 1570233 19690606 FR DE 1770672 DE GB 1188889 GB

- L4 ANSWER 155 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Metal oxide films

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11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 1167128		19691015	GB	
	FR 1572757			FR	
	US 3477936		19690000	US	

- L4 ANSWER 156 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Gas-chromatographic analysis of aerosols by pressurized liquid sampling
- L4 ANSWER 157 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hair waving, two phase, quick breaking, aerosol foam
 PATENT NO. KIND DATE APPLICATION NO. DATE
 PI US 3433868 A 19690318 US 1964-385467 19640727
- L4 ANSWER 158 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- Concentration of sea water and brine by the gas hydration process. XIV.

 Pressure and temperature diagrams of mixed hydrating agents
- L4 ANSWER 159 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Careful removal of acetylene and difluroethane from vinyl fluoride
- L4 ANSWER 160 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Studies on explosions. I

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L4
     ANSWER 161 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
     Conversion of hydrocarbons by hydrogen
                                    APPLICATION NO.
                KIND DATE
                                                              DATE
     PATENT NO.
                              _____
                                         _____
                                                               _____
     ______
                       ----
                              19640117
                                         FR
                                                               19620408
PΙ
     FR 1349148
     ANSWER 162 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Effect of anions on the electrocrystallization of zinc and cadmium
ΤI
     ANSWER 163 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
     The electrochemical fluorination of organosilicon compounds
TT
    ANSWER 164 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant mixture of dichlorodifluoromethane and difluoroethane
TΙ
                KIND DATE APPLICATION NO. DATE
    PATENT NO.
     -----
    US 23358
                             19510417
                                         US
PΙ
    ANSWER 165 OF 214 USPATFULL on STN
L4
      Materials and methods for the conversion of hydrofluorocarbons
TI
      US 2005288536 A1 20051229
PΙ
    ANSWER 166 OF 214 USPATFULL on STN
L4
      Process for making polyurethane and polyisocyanurate foams using
TT
      mixtures of a hydrofluorocarbon and methyl formate as a blowing agent
      US 2005277701
                     A1 20051215
PΙ
    ANSWER 167 OF 214 USPATFULL on STN
L4
тT
      Topical spray compositions
                  B1 20051108
PΙ
      US 6962691
    ANSWER 168 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
TΙ
      US 2005218371 A1 20051006
PΙ
    ANSWER 169 OF 214 USPATFULL on STN
L4
ΤI
      Refrigerant composition .
      US 2005109977 A1 20050526
PΙ
    ANSWER 170 OF 214 USPATFULL on STN
L4
      Closed cycle refrigeration system and mixed component refrigerant
TT
      US 2005086950
PΙ
                    A1 20050428
    ANSWER 171 OF 214 USPATFULL on STN
L4
      Etchant with selectivity for doped silicon dioxide over undoped silicon
TТ
      dioxide and silicon nitride, processes which employ the etchant, and
      structures formed thereby
PΙ
      US 6875371
                      B1 20050405
    ANSWER 172 OF 214 USPATFULL on STN
L4
ΤI
      Heat transfer fluids and methods of making and using same
PΤ
      US 2004227125
                      A1 20041118
    ANSWER 173 OF 214 USPATFULL on STN
L4
TТ
      Topical spray compositions
PΙ
      US 2004213744
                      A1 20041028
L4
    ANSWER 174 OF 214 USPATFULL on STN
TI
      Formulations of mometasone and a bronchodilator for pulmonary
      administration
PΙ
      US 2004198708
                     A1 20041007
    ANSWER 175 OF 214 USPATFULL on STN
L4
TI
      Sol-gel-derived halogen-doped glass
PΙ
      US 2004194511
                      A1 20041007
    ANSWER 176 OF 214 USPATFULL on STN
L4
ΤI
      Materials and methods for the conversion of hydrofluorocarbons
```

```
PΙ
       US 2004127757
                          A1
                               20040701
1.4
     ANSWER 177 OF 214 USPATFULL on STN
       Method for plasma etching performance enhancement
ΤI
       US 2004072443
                                20040415
PΙ
                          A1
       US 6833325
                          B2
                                20041221
L4
     ANSWER 178 OF 214 USPATFULL on STN
       Methods for etching photolithographic reticles
ΤI
       US 2004072081
                               20040415
PΙ
                          A1
     ANSWER 179 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
ΤI
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
рT
       US 2003203639
                          A1
                               20031030
     ANSWER 180 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TΤ
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
       US 6537922
                               20030325
PΤ
                          B1
     ANSWER 181 OF 214 USPATFULL on STN
L4
       Variable load refrigeration system particularly for cryogenic
TΤ
       temperatures
       US 6426019
                          В1
                               20020730
PΤ
     ANSWER 182 OF 214 USPATFULL on STN
L4
       Formulations of mometasone and a bronchodilator for pulmonary
TI
       administration
PΙ
       US 2002076382
                          A1
                               20020620
     ANSWER 183 OF 214 USPATFULL on STN
L4
       Substrate cleaning apparatus and method
TΤ
       US 2002072016
PΤ
                         A1
                              20020613
                          В2
       US 6692903
                               20040217
     ANSWER 184 OF 214 USPATFULL on STN
L4
       Apparatus for providing ozonated process fluid and methods for using
TI
       same
       US 2002066717
                               20020606
PΤ
                          A1
L4
     ANSWER 185 OF 214 USPATFULL on STN
ΤI
       Lubricant refrigerant composition for hydrofluorocarbon (HFC)
       refrigerants
       US 6374629
ΡI
                          B1
                               20020423
     ANSWER 186 OF 214 USPATFULL on STN
L4
ΤI
       High-density plasma etching of carbon-based low-k materials in a
       integrated circuit
                          B1
PΙ
       US 6284149
                               20010904
     ANSWER 187 OF 214 USPATFULL on STN
L4
       Flower-like capacitor structure for a memory cell
TI
ΡI
       US 6281542
                          В1
                               20010828
     ANSWER 188 OF 214 USPATFULL on STN
TΙ
       Etchant with selectivity for doped silicon dioxide over undoped silicon
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
PΙ
       US 6117791
                               20000912
     ANSWER 189 OF 214 USPATFULL on STN
L4
       Aerosol cosmetic compositions, aerosols containing them and uses
TΙ
PΙ
       US 6113923
                               20000905
     ANSWER 190 OF 214 USPATFULL on STN
L4
       Fluorine assisted stripping and residue removal in sapphire downstream
TΤ
```

plasma asher PΙ US 6082374 20000704 ANSWER 191 OF 214 USPATFULL on STN 1.4 Variable load refrigeration system particularly for cryogenic TI temperatures 20000620 PΤ US 6076372 ANSWER 192 OF 214 USPATFULL on STN L4Process for the reduction of chlorofluorocarbons and production of ΤI derivatives thereof in an electrolytic cell, cell for carrying out said reduction and process for removing the by-products formed within the cell US 6068756 20000530 PΤ WO 9724162 19970410 ANSWER 193 OF 214 USPATFULL on STN L4Fixative vinyl acetate tetrapolymers TI 19981103 PΤ US 5830439 ANSWER 194 OF 214 USPATFULL on STN 1.4 Method for etching dielectric using fluorohydrocarbon gas, NH.sub.3 ΤI -generating gas, and carbon-oxygen gas 19980929 US 5814563 PΙ ANSWER 195 OF 214 USPATFULL on STN L4Spray formulation for the testing of smoke detectors TI19980728 PΤ US 5785891 ANSWER 196 OF 214 USPATFULL on STN L4Antiperspirant aerosol composition with high solids content ΤI PΙ US 5605682 19970225 ANSWER 197 OF 214 USPATFULL on STN Hydrogen fluoride dopant source in the preparation of conductive coated TТ substrate PΙ US 5496583 19960305 L4ANSWER 198 OF 214 USPATFULL on STN Working fluid containing difluoroethane TI PΙ US 5433879 19950718 ANSWER 199 OF 214 USPATFULL on STN T.4 Manufacture of rigid foams and compositions therefor TΤ US 5391584 19950221 PΤ ANSWER 200 OF 214 USPATFULL on STN T.4 Topical medicinal pressurized aerosol compositions and method of TI preparation, method of use and article of manufacture thereof PΙ US 5378451 19950103 ANSWER 201 OF 214 USPATFULL on STN L4 ΤI Gaseous doping of tungsten oxide PΙ US 5324537 19940628 L4ANSWER 202 OF 214 USPATFULL on STN TΙ Working fluid PΙ US 5304319 19940419 L4 ANSWER 203 OF 214 USPATFULL on STN TI Anti-reflective coatings comprising light metal fluorides PΙ US 5208101 19930504 ANSWER 204 OF 214 USPATFULL on STN L4Process for etching ΤI ΡI US 5110408 19920505 ANSWER 205 OF 214 USPATFULL on STN L4 TI Process for the preparation of polyurethane rigid foams having a low

thermal conductivity and their use ΡI US 5096933 ANSWER 206 OF 214 USPATFULL on STN L4 Production of ion beams by chemically enhanced sputtering of solids TI 19920218 US 5089746 PΙ ANSWER 207 OF 214 USPATFULL on STN L4Process for restoring deactivated catalysts ΤI 19900626 PΙ US 4937215 ANSWER 208 OF 214 USPATFULL on STN L4 Process for protecting electrochemical sensors from biofouling in an ΤI aquatic environment 19880816 ΡI US 4763537 ANSWER 209 OF 214 USPATFULL on STN L4Aerosol waterproof sunscreen compositions ΤI US 4686099 19870811 ΡI ANSWER 210 OF 214 USPATFULL on STN L4Preparation of non-flammable aerosol propellant microemulsion system TI US 4655959 19870407 PΙ ANSWER 211 OF 214 USPATFULL on STN L4Non-flammable aerosol propellant microemulsion system ΤI PΙ US 4536323 19850820 ANSWER 212 OF 214 USPATFULL on STN L4Gas for selectively etching silicon nitride and process for selectively ΤI etching silicon nitride with the gas PΙ US 4529476 19850716 ANSWER 213 OF 214 USPATFULL on STN L4Hydrotreating vacuum gas oils with catalyst and added organic fluorine TIcompound PΙ US 4420388 19831213 L4 ANSWER 214 OF 214 USPATFULL on STN HYDROCRACKING CATALYST ACTIVATION TREATMENT TIPΙ US 3673108 19720627

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Welcome to STN International! Enter x:x
LOGINID:ssspta1751gxw
PASSWORD:
TERMINAL (ENTER 1, 2, 3, OR ?):2
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      3
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         DEC 14 2006 MeSH terms loaded for MEDLINE file segment of TOXCENTER
NEWS 5
         DEC 14 CA/CAplus to be enhanced with updated IPC codes
NEWS
         DEC 21 IPC search and display fields enhanced in CA/CAplus with the
NEWS 7
                 IPC reform
         DEC 23
                 New IPC8 SEARCH, DISPLAY, and SELECT fields in USPATFULL/
NEWS
      8
                 USPAT2
                 IPC 8 searching in IFIPAT, IFIUDB, and IFICDB
NEWS 9
         JAN 13
                 New IPC 8 SEARCH, DISPLAY, and SELECT enhancements added to
NEWS 10
         JAN 13
                 INPADOC
         JAN 17
                 Pre-1988 INPI data added to MARPAT
NEWS 11
         JAN 17
                 IPC 8 in the WPI family of databases including WPIFV
NEWS 12
NEWS 13
         JAN 30
                 Saved answer limit increased
NEWS 14
                 Monthly current-awareness alert (SDI) frequency
         JAN 31
                 added to TULSA
         FEB 21 STN AnaVist, Version 1.1, lets you share your STN AnaVist
NEWS 15
                 visualization results
                 Status of current WO (PCT) information on STN
NEWS 16 FEB 22
NEWS 17 FEB 22
                 The IPC thesaurus added to additional patent databases on STN
NEWS 18 FEB 22 Updates in EPFULL; IPC 8 enhancements added
NEWS 19 FEB 27
                 New STN AnaVist pricing effective March 1, 2006
NEWS 20 FEB 28 MEDLINE/LMEDLINE reload improves functionality
NEWS 21
         FEB 28
                 TOXCENTER reloaded with enhancements
NEWS 22
         FEB 28
                 REGISTRY/ZREGISTRY enhanced with more experimental spectral
                 property data
NEWS 23
         MAR 01
                 INSPEC reloaded and enhanced
NEWS EXPRESS
             FEBRUARY 15 CURRENT VERSION FOR WINDOWS IS V8.01a,
              CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0jc(jp),
              AND CURRENT DISCOVER FILE IS DATED 19 DECEMBER 2005.
              V8.0 AND V8.01 USERS CAN OBTAIN THE UPGRADE TO V8.01a AT
              http://download.cas.org/express/v8.0-Discover/
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              CAS World Wide Web Site (general information)
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=> s difluoroethane/cn

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=> file req

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SINCE FILE TOTAL ENTRY SESSION 0.21 0.21

FULL ESTIMATED COST

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TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006

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* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added, *
* effective March 20, 2005. A new display format, IDERL, is now *

* available and contains the CA role and document type information. *

Structure search iteration limits have been increased. See HELP SLIMITS for details.

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http://www.cas.org/ONLINE/UG/regprops.html

=> s difluoroethane/cn

L1 1 DIFLUOROETHANE/CN

=> s trifluoromethyl iodide/cn

L2 1 TRIFLUOROMETHYL IODIDE/CN

=> file caplus,uspatful
COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION 9.96 10.17

FULL ESTIMATED COST

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```
=> s 11 and 12
1.3
            0 L1 AND L2
=> s l1
          214 L1
1.4
=> s 12
         2027 L2
L5
=> s 14 and 15
            0 L4 AND L5
=> file reg
                                              SINCE FILE
                                                              TOTAL
COST IN U.S. DOLLARS
                                                   ENTRY
                                                            SESSION
                                                    1.97
FULL ESTIMATED COST
                                                              12.14
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provided by InfoChem.
                         1 MAR 2006 HIGHEST RN 875609-25-9
STRUCTURE FILE UPDATES:
                         1 MAR 2006 HIGHEST RN 875609-25-9
DICTIONARY FILE UPDATES:
New CAS Information Use Policies, enter HELP USAGETERMS for details.
TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006
  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added,
* effective March 20, 2005. A new display format, IDERL, is now
 available and contains the CA role and document type information.
******************
Structure search iteration limits have been increased. See HELP SLIMITS
for details.
REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document. For information
on property searching in REGISTRY, refer to:
http://www.cas.org/ONLINE/UG/regprops.html
=> d his
     (FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)
    FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006
Ll
             1 S DIFLUOROETHANE/CN
L2
             1 S TRIFLUOROMETHYL IODIDE/CN
    FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
L3
             0 S L1 AND L2
L4
           214 S L1
          2027 S L2
L5
L6
             0 S L4 AND L5
```

```
FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006
=> d l1
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
L1
     25497-28-3 REGISTRY
RN
     Entered STN: 16 Nov 1984
ED
     Ethane, difluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
CN
OTHER NAMES:
    Difluoroethane
CN
     C2 H4 F2
MF
     IDS, COM
CI
                  BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMLIST, CIN, DETHERM*,
     STN Files:
LC
       ENCOMPLIT, ENCOMPLIT2, ENCOMPPAT, ENCOMPPAT2, IFICDB, IFIPAT, IFIUDB,
       NIOSHTIC, PDLCOM*, PIRA, PROMT, TOXCENTER, TULSA, USPAT2, USPATFULL, VTB
         (*File contains numerically searchable property data)
1/2 H<sub>3</sub>C-CH<sub>3</sub>
     D1-F
**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**
             164 REFERENCES IN FILE CA (1907 TO DATE)
             164 REFERENCES IN FILE CAPLUS (1907 TO DATE)
               3 REFERENCES IN FILE CAOLD (PRIOR TO 1967)
=> d 12
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
     2314-97-8 REGISTRY
     Entered STN: 16 Nov 1984
     Methane, trifluoroiodo- (6CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
CN
    Freon 13I1
    Iodotrifluoromethane
CN
CN
    Monoiodotrifluoromethane
    Perfluoromethyl iodide
CN
CN
    R 13I1
    Trifluoroiodomethane
CN
CN
     Trifluoromethyl iodide
FS
     3D CONCORD
DR
     263005-66-9
MF
     C F3 I
CI
     COM
                  BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS,
LC
     STN Files:
       CHEMINFORMRX, CHEMLIST, CHEMSAFE, CIN, CSCHEM, CSNB, DETHERM*, DIPPR*,
       GMELIN*, IFICDB, IFIPAT, IFIUDB, MEDLINE, MSDS-OHS, PROMT, PS, RTECS*,
       SPECINFO, TOXCENTER, ULIDAT, USPAT2, USPATFULL, VTB
```

(*File contains numerically searchable property data)

(**Enter CHEMLIST File for up-to-date regulatory information)

EINECS**, NDSL**, TSCA**

Other Sources:

```
1837 REFERENCES IN FILE CA (1907 TO DATE)
```

- 12 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
- 1839 REFERENCES IN FILE CAPLUS (1907 TO DATE)
 - 88 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

=> d his

L1

L3

(FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006

1 S DIFLUOROETHANE/CN

L2 1 S TRIFLUOROMETHYL IODIDE/CN

FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006

0 S L1 AND L2

L4 214 S L1

L5 2027 S L2

L6 0 S L4 AND L5

FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006

=> d 14 ti,pi

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT NO.			KIND DATE			APPLICATION NO.						DATE				
				-				-									
ΡI	US 2005	277701		A1		2005	1215	1	US 2	004-	8684	00		20040615			
	WO 2006	002043		A1 20060105		1	WO 2	005-1	US20:	929		20050614					
	W:	AE, AG,	AL,	AM,	AT,	AU,	ΑZ,	BA,	BB,	BG,	BR,	BW,	BY,	ΒZ,	CA,	CH,	
		CN, CO,	CR,	CU,	CZ,	DΕ,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,	
		GE, GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	ΚE,	KG,	KM,	ΚP,	KR,	ΚZ,	
		LC, LK,	LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK,	MN,	MW,	MX,	ΜZ,	NA,	
		NG, NI,	NO,	ΝZ,	OM,	PG,	PH,	PL,	PT,	RO,	RU,	SC,	SD,	SE,	SG,	SK,	
		SL, SM,	SY,	TJ,	TM,	TN,	TR,	TT,	TZ,	UA,	UG,	US,	UΖ,	VC,	VN,	YU,	
		ZA, ZM,	zw														
	RW:	AT, BE,	BG,	CH,	CY,	CZ,	DE,	DK,	EE,	ES,	FI,	FR,	GB,	GR,	ΗU,	ΙE,	
		IS, IT,	LT,	LU,	MC,	NL,	PL,	PT,	RO,	SE,	SI,	SK,	TR,	BF,	ВJ,	CF,	
		CG, CI,	CM,	GΑ,	GN,	GQ,	GW,	ML,	MR,	NE,	SN,	TD,	TG,	BW,	GH,	GM,	
		KE, LS,	MW,	MZ,	NA,	SD,	SL,	SZ,	TZ,	ŪĠ,	ZM,	ZW,	AM,	ΑZ,	BY,	KG,	
		KZ, MD,	RU,	TJ,	TM												

=> d l4 ti,pi 1-YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y)/N:y

YOU HAVE REQUESTED DATA FROM 214 ANSWERS - CONTINUE? Y/(N):y

L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT NO.			KIND DATE			APPLICATION NO.					DATE						
PI US 200			5277701		A1	A1 20051215		US 2004-868400 WO 2005-US20929					20040615					
	WO 2006002043			A1 20060105									20050614					
		W:	ΑE,	AG,	ΑL,	AM,	ΑT,	AU,	ΑZ,	BA,	BB,	BG,	BR,	BW,	BY,	ΒZ,	CA,	CH,
			CN,	CO,	CR,	CU,	CZ,	DE,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,
			GE,	GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JΡ,	KE,	KG,	KM,	ΚP,	KR,	ΚZ,
			LC,	LK,	LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK.	MN.	MW.	MX.	MZ.	NA.

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SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU,
            ZA, ZM, ZW
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF,
            CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM,
            KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG,
            KZ, MD, RU, TJ, TM
    ANSWER 2 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Procedure for processing hollow glassware, particularly a bottle
ΤI
    PATENT NO.
                       KIND DATE
                                    APPLICATION NO.
                       ----
                              -----
                                         ______
                                                               -----
                                        AT 2003-941
                              20040615
                                                               20030617
PΙ
    AT 200300941
                        A5
    AT 412341
                        В
                              20050125
    ANSWER 3 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Preparation method and equipment of difluorochloroethane
                       KIND DATE APPLICATION NO.
                                                              DATE
    PATENT NO.
                                         -----
     -----
                       ----
                              -----
                              20041222 CN 2004-10015778
    CN 1556083
                        Α
                                                               20040109
PΙ
    ANSWER 4 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant composition with lubricant
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
                                                             DATE
                            -----
                              20050512 WO 2004-US34724
                      . ____
     _____
    WO 2005042679 A1
                                                             20041020
PΙ
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            SN, TD, TG
    US 2005109977
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                        A1
                                                               20041020
    ANSWER 5 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Closed cycle refrigeration system and mixed component refrigerant
    PATENT NO.
                       KIND DATE APPLICATION NO. DATE
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PΙ
    US 2005086950
                        A1
                              20050428
                                         US 2003-694699
                                                              20031028
    ANSWER 6 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
    Improvements in or relating to aerosol formulations comprising formoterol
ΤI
    fumarate dihydrate
                                      APPLICATION NO.
                       KIND
                             DATE
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    WO 2005034927
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                              20050421
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            SN, TD, TG
L4
    ANSWER 7 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Consolidation heat treating atmospheres for manufacture of sol-gel-derived
TI
    halogen-doped optical glass
    PATENT NO.
                       KIND
                             DATE
                                         APPLICATION NO.
                                                               DATE
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NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK,

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    US 2004194511 A1
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    US 2003147605
                        A1
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                                           US 2002-62748
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                        B2
    US 6928220
                               20050809
                                                                  20020807
                        A1
                               20030807
                                           US 2002-215162
    US 2003147606
    ANSWER 8 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Polyol compositions containing polyether or polyester polyols and
ΤI
     polyisocyanate-based foams prepared therefrom
     PATENT NO. KIND DATE APPLICATION NO.
    EP 1435366 A1 20040707 EP 2003-250046
                                                                 20030103
PΙ
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20040729 WO 2003-US41607 20031223
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     BR 2003017211
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                                                                 20031223
    ANSWER 9 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Materials and methods for the conversion of hydrofluorocarbons to
ΤI
     fluoromonomers
                       KIND DATE
                                      APPLICATION NO.
    US 2004127757 A1 20040701 US 2002-331821 20021230 CA 2511887 AA 20040722 CA 2003-2511887 20031230 WO 2004060842 A1 20040722 WO 2003-US41851 20031230 WO 2004060842 C1 20041021
ΡI
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                        A1 20051005 EP 2003-815021 20031230
    EP 1581468
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                               20051229 US 2005-218055
                                                                  20050831
     US 2005288536
                         A1
    ANSWER 10 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Plasma device and procedure for anisotropic etching in of structures in a
TI
     substrate
                      KIND DATE APPLICATION NO.
     PATENT NO.
    DE 10247913
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                                           ______
                       A1
A2
A3
                               20040422 DE 2002-10247913 20021014
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                                           WO 2003-DE2971
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                         A2 20050720 EP 2003-753277
    EP 1554747
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                                        JP 2004-543938
                         T2
                               20060126
     JP 2006503425
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L4

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Procedure for the plasma anisotropic etching of a silicon substrate
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                              20040422 DE 2002-10246063
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PΙ
                        A1
    ANSWER 12 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Method for plasma etching performance enhancement in semiconductor device
TI
    fabrication
                      KIND DATE APPLICATION NO.
                                                               DATE
    PATENT NO.
    US 2004072443 A1 20040415
                                         _____
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                                         US 2002-295601
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    US 6833325 B2 20041221

US 2004072430 A1 20040415 US 2003-674675 20030929

WO 2004034445 A2 20040422 WO 2003-US31712 20031006

WO 2004034445 A3 20040812

WO 2004034445 B1 20040930
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    AU 2003282718 A1 20040504 AU 2003-282718 20031006 EP 1550153 A2 20050706 EP 2003-774602 20031006
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                                         US 2004-946181
    US 2005037624
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                                                               20040920
T.4
    ANSWER 13 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤТ
    Method for etching photolithographic reticles
    PATENT NO. KIND DATE APPLICATION NO. DATE
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    JP 2004038154 A2 20040205 JP 2003-136222 20030514
ΡI
                       A1 20040415 US 2003-437729
    US 2004072081
    ANSWER 14 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Safety tires having good durability and riding comfort
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
                                         ______
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PΙ
    JP 2003118311
                       A2
                              20030423 JP 2002-94474
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    ANSWER 15 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Silicon dioxide etching yield measurements with inductively coupled
    fluorocarbon plasmas
L4
    ANSWER 16 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Speed-of-sound, ideal-gas heat capacity, and second acoustic virial
TI
    coefficient for mixing refrigerant difluoroethane (HFC152a) +
    difluoromethane (HCFC22)
    ANSWER 17 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Resistive plate chambers for muon detection at LHC
    ANSWER 18 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Heat transfer fluids useable for cooling items, such as optical fibers
    PATENT NO. KIND DATE APPLICATION NO. DATE
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    WO 2002074709
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US 2004-874079
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                             20051006
    US 2005218371
    ANSWER 19 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Algorithmically Compressed Data and the Topological Conjecture for the
TI
    Inner-Core Electrons
    ANSWER 20 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Substrate cleaning apparatus and method
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                   KIND DATE APPLICATION NO.
                                                           DATE
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    US 2002072016 A1 20020613 US 2000-737373
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PI
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    US 6692903
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WO 2002049078 A3
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                                                            20011210
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            PT, SE, TR
    ANSWER 21 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Hydrocarbon-based refrigerant mixture composition for replacing R-12 and
TI
    R-22 refrigerants
    PATENT NO.
                      KIND
                            DATE
                                     APPLICATION NO.
                                                           DATE
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                                       KR 2000-17251
    KR 2000036953
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                             20000705
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PΙ
    ANSWER 22 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Formulations of mometasone and a bronchodilator for pulmonary
TΙ
    administration
                                     APPLICATION NO.
                     KIND DATE
                                                           _____
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    WO 2002011711
                      A2 20020214 WO 2001-US24093
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    CA 2417973
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    AU 2001078115
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                      A1 20020620 US 2001-920340
A2 20030521 EP 2001-956079
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    EP 1311294
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    US 2004198708
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    ANSWER 23 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Detection of fluorine containing gas compounds
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    PATENT NO. KIND DATE APPLICATION NO.
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ΡI
    JP 2002022725
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    JP 3640601
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T.4
    ANSWER 24 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
    Additivity of the Correlation Energy in Some 3D Organic Molecules
L4
    ANSWER 25 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Fluorohydrocarbon etchant with selectivity for doped silicon dioxide over
TI
    undoped silicon dioxide and silicon nitride, processes which employ the
    etchant, and structures formed thereby
    PATENT NO. KIND DATE APPLICATION NO.
                                                            -----
    WO 2002003439
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PΙ
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                          A2 20030402 EP 2001-956164
     EP 1297564
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     JP 2004503082
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     ANSWER 26 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
     Fabrication of electric circuits by reactive-gas etching of masked metal
     layers on substrates
                                           APPLICATION NO.
     PATENT NO. KIND
                                DATE
                                                                     DATE
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                                           JP 2002-511020
US 2001-24958
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     ANSWER 27 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     High-density plasma etching of carbon-based low-k materials in an
TI
     integrated circuit
                                 DATE APPLICATION NO.
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ΡI
     US 6284149
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                                                                    19980918
     ANSWER 28 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Flower-like capacitor structure for a memory cell
ΤI
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                                                                    DATE
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US 5973350 A 19991026 US 1998-60565 19980414
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     ANSWER 29 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Apparatus for providing ozonated process fluid and methods for using same
ΤI
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     WO 2001040124 A1 20010607 WO 2000-US42449 20001201 WO 2001040124 C2 20020808
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                                 20020606 US 2000-727661 20001201
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     ANSWER 30 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Cooling agent
ΤI
                                        APPLICATION NO. DATE
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     RU 2135541
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ANSWER 31 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4 Fluoroethane etchant with selectivity for doped silicon dioxide over ΤI undoped silicon dioxide and silicon nitride, processes which employ the etchant, and structures formed for semiconductor devices KIND DATE APPLICATION NO. PATENT NO. -----_ _ _ _ -----Α 20000912 US 1998-102152 19980622 PΙ US 6117791 В1 20030325 US 2000-625144 20000725 US 6537922 В1 20050405 US 2000-711324 20001113 US 6875371 20031030 US 2003-396164 20030325 A1 US 2003203639 ANSWER 32 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Evaluation of pentafluoroethane and 1,1-difluoroethane for a dielectric ΤI etch application in an inductively coupled plasma etch tool ANSWER 33 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Topical sprays containing film-forming polymers ΤI PATENT NO. KIND DATE APPLICATION NO. DATE _____ ----------_ _ _ _ 20000810 WO 2000-GB366 20000207 WO 2000045795 A2 PΙ WO 2000045795 A3 20010809 W: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW RW: GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG 20011020 IN 1999-BO93 19990205 IN 186668 Α CA 2359640 AA 20000810 CA 2000-2359640 20000207 AU 2000024472 A5 20000825 AU 2000-24472 20000207 AU 759515 B2 20030417 Α BR 2000007997 20011030 BR 2000-7997 20000207 EP 1150661 A2 20011107 EP 2000-902727 20000207 B1 20031022 EP 1150661 AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO T2 20021029 JP 2000-596915 20000207 JP 2002536319 NZ 2000-513208 20000207 NZ 513208 Α 20030530 E AT 2000-902727 20000207 AT 252380 20031115 ${f T}$ PT 2000-902**727** PT 1150661 20040227 20000207 T3

A ZA 2000005727 20001221 ZA 2000-5727 20001017 NO 2001-3815 NO 2001003815 Α 20011002 20010803 HK 2002-103295 HK 1042043 A1 20040408 20020502 US 2004213744 A1 20041028 US 2003-686517 20031016 ANSWER 34 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4 Synthetic lubricating oil-C1-3-hydrofluorocarbon refrigerant combinations TIfor low-temperature phase separation in refrigeration compressor units PATENT NO. KIND DATE APPLICATION NO. DATE ______ ----20000727 WO 1999-US31118 PΙ WO 2000043464 **A1** 19991228

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US 2000-503843

W: AU, CA RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE US 6374629 B1 20020423 US 1999-2367**07** 19990125 CA 2360536 AΑ 20000727 CA 1999-2360536 19991228 EP 1153099 A1 20011114 EP 1999-968**562** 19991228 EP 1153099 20040929 В1 AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI AU 774378 20040624 AU 2000-25954 19991228 B2

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ANSWER 35 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Variable load refrigeration system particularly for cryogenic temperatures

	PATENT NO.	KIND	DATE		
ΡI	US 6076372	Δ	20000620	110 1998-222809	19981230
PI	MX 9911766	A A	20000620 20000731	MX 1999-11766	19991215
	ZA 9907869	A A	20000705	ZA 1999-7869	19991223
	CA 2293191	С	20040921	CA 1999-2293191	
	CA 2293191	AA	20000630		
	TW 430733	AA B A2	20010421	TW 1999-88123007	
	EP 1016839	A2		EP 1999-126062	19991228
	EP 1016839		20001102		
	EP 1016839	B1	20030709	GB, GR, IT, LI, LU, NL,	SE MC DT
	R: AT, BE, CI IE, SI, L'			GB, GR, 11, L1, L0, ND,	SE, MC, FI,
	JP 2000205675		20000728	JP 1999-373465	19991228
			20050803		
	BR 9905991	A	20000905	BR 1999-5991	19991228
	BR 9905991 CN 1265462 AT 244860	A	20000906	BR 1999-5991 CN 1999-127429	19991228
	AT 244860	E	20030715	AT 1999-126062	19991228
	ES 2197568	Т3	20040101	ES 1999-126 062	
	AU 9965541	A1	20000706	AU 1999-65541 US 2000-545670	19991230
	AU 753979	B2	20021031		
	US 6426019	B1	20020730	US 2000-545670	20000407
				US 2002-201 287	20020724
	US 6881354	B2	20050419		
L4 TI	ANSWER 36 OF 214 A process for disp				
L4	ANSWER 37 OF 214	CADLIIG	CODVETCHT	2006 ACS on STN	
ΤΙ				of glass via fiber elon	gation
L4	ANSWER 38 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI				rodifluoromethane and	
	chlorodifluoromet	nane over	nickel c	atalysts	
L4	ANSWER 39 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
L4 TI				2006 ACS on STN	
TI	Accidental release	e prevent	ion		
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TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepatent NO. US 5830439 US 5972329 WO 9851266	CAPLUS COSITION KIND A1 J, MD, PL CAPLUS Etate tet KIND A A A	DATE 19990304 , SK, UA, COPYRIGHT rapolymers DATE 19981103 19991026 19981119	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318	DATE
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepatent No. US 5830439 US 5972329 WO 9851266 WO 9851266	CAPLUS CAPLUS CAPLUS A1 J, MD, PL CAPLUS CAP	DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 19981119 19990218	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318	DATE 19970516 19980304 19980318
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepatent No. US 5830439 US 5972329 WO 9851266 WO 9851266 W: AL, AM, AM	CAPLUS COSITION KIND A1 J, MD, PL CAPLUS Etate tet KIND A A A A2 A3 T, AU, AZ	DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 19981119 19990218 , BA, BB,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN,	DATE 19970516 19980304 19980318 CU, CZ, DE,
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp Example 10 of 214 Fixative vinyl accepation of the cooling agent comp ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl accepation of the cooling agent comp BY, CZ, HO ANSWER 41 OF 214 Fi	CAPLUS COSITION KIND A1 J, MD, PL CAPLUS Etate tet KIND A A A A2 A3 G, AU, AZ S, FI, GB Z, LC, LK	DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK,	DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX,
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. US 5830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KZ NO, NZ, PI	CAPLUS CA	DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ,	DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT,
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. US 5830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KZ NO, NZ, PI UA, UG, UZ	CAPLUS COSITION KIND A1 J, MD, PL CAPLUS	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU,	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM
TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. US 5830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KZ NO, NZ, PI UA, UG, UZ RW: GH, GM, KI	CAPLUS CA	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE,	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI,
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TI L4 TI PI L4 TI	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. US 5830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KA NO, NZ, PI UA, UG, UA RW: GH, GM, KI FR, GB, GI GA, GN, MI	CAPLUS COSITION KIND A1 J, MD, PL CAPLUS Etate tet KIND A A A A A A A A C, AU, AZ G, FI, GB Z, LC, LK L, PT, RO Z, VN, YU E, LS, MW R, IE, IT L, MR, NE	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD,	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
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TI L4 TI PI L4 TI .	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. S830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KN NO, NZ, PN UA, UG, UN RW: GH, GM, KN FR, GB, GN GA, GN, MN AU 9868659 ANSWER 42 OF 214 Selective etching	CAPLUS CA	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208 COPYRIGHT ctrics us:	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG AU 1998-68659 2006 ACS on STN ing fluorohydrocarbon ga	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI .	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. S830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KN NO, NZ, PN UA, UG, UN RW: GH, GM, KN FR, GB, GN GA, GN, MN AU 9868659 ANSWER 42 OF 214 Selective etching NH3-generating gas	CAPLUS CA	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208 COPYRIGHT ctrics us: rbon-oxyge	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG AU 1998-68659 2006 ACS on STN ing fluorohydrocarbon gaen gas	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI .	Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HO ANSWER 41 OF 214 Fixative vinyl acc PATENT NO. S830439 US 5972329 WO 9851266 W: AL, AM, AM DK, EE, ES KP, KR, KN NO, NZ, PN UA, UG, UN RW: GH, GM, KN FR, GB, GN GA, GN, MN AU 9868659 ANSWER 42 OF 214 Selective etching NH3-generating gas	CAPLUS CA	COPYRIGHT DATE 19990304 , SK, UA, COPYRIGHT rapolymer: DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208 COPYRIGHT ctrics us: rbon-oxyge DATE	2006 ACS on STN APPLICATION NO. WO 1997-RU274 US 2006 ACS on STN APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318 BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG AU 1998-68659 2006 ACS on STN ing fluorohydrocarbon gaen gas	DATE 19970826 DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318 s, DATE

	US 5843847	A 19981201	US 1996-639388	19960429
	JP 10041274	A2 19980213	JP 1997-112887	19970430
	JP 10056001	A2 19980224	JP 1997-147995	19970605
	EP 813233	A2 19971217	JP 1997-112887 JP 1997-147995 EP 1997-304035	19970610
	EP 813233	A3 19990825		
	R: AT, BE, CH, IE, FI	DE, DK, ES, FR, GB	, GR, IT, LI, LU, NL, S	E, MC, PT,
L4	ANSWER 43 OF 214 C	APLUS COPYRIGHT 20	06 ACS on STN	
TI	Spray formulation for	or testing of smoke	detectors	
	DATENT NO	KIND DATE	APPLICATION NO.	DATE
ΡI	US 5785891	A 19980728	US 1996-713058	19960912
L4 TI	ANSWER 44 OF 214 C. Coolant agent compo		06 ACS on STN	
11	PATENT NO.	KIND DATE	APPLICATION NO.	DATE
PI	RU 2098445	C1 19971210	RU 1996-104188	19960301
L4 TI	PATENT NO.	s for fluorine-assi KIND DATE	06 ACS on STN sted stripping and resi APPLICATION NO.	due removal DATE
ΡI			WO 1997-US16886	
	RW: AT, BE, CH, EP 868836	A1 19981007	, GB, GR, IE, IT, LU, M EP 1997-944360	19970924
	JP 2000501573	T2 20000208	JP 1998-515793 US 1997-936548	19970924
	US 6082374	A 20000704	US 1997-936548	19970924
TI L4	trifluoroethane on ANSWER 47 OF 214 C	lead cathodes combi		sion anodes
TI	derivatives thereof	in an electrolytic	orocarbons and producti cell, cell for carryin byproducts formed with	g out said
	PATENT NO.	KIND DATE		DATE
PI	WO 9724162		WO 1996-ES248	19961226
			, GB, GR, IE, IT, LU, M	C, NL, PT, SE 19951228
	ES 2103207 ES 2103207	B1 19980401	ES 1995-2533	
	EP 819448 EP 819448	A1 19980121 B1 20000517	EP 1996-941667	19961226
	R: AT, BE, CH, IE, FI	DE, DK, ES, FR, GB	, GR, IT, LI, LU, NL, S	E, MC, PT,
	AT 192939		AT 1996-941667	19961226
			ES 1996-941667 US 1997-913389	
	05 0000750	A 20000550	03 1337 313303	155/1104
L4 TI		e doped textured tr	06 ACS on STN ansparent conducting Sn ical vapor deposition	O2 films
L4	ANSWER 49 OF 214 C	APLUS COPYRIGHT 20	06 ACS on STN	
TI			or leakage detection APPLICATION NO.	DATE
ΡI	JP 08245952		JP 1995-51647	19950313
T 4	NYOURD EA AT AT A		0.C 2.CC CEN	
L4 TI	ANSWER 50 OF 214 C. Evaluation of critic		06 ACS on STN alohydrocarbons and its	quality

US 5843847

codes

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19981201

US 1996-639388

19960429

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ANSWER 51 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Single-phase aerosol antiperspirant composition
    PATENT NO. KIND DATE APPLICATION NO. DATE
WO 9618378 A2 19960620 WO 1995-US16286 19951214
                                                             -----
PΙ
        W: AU, BR, CA, CH, CN, DE, ES, FI, GB, JP, KR, NO, NZ, PL, PT, RO,
           RU, SE, UA, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                   A1 19960703 AU 1996-49618
    AU 9649618
    ANSWER 52 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Ab initio studies of fluorinated ethanes: electronic and energetic
ΤI
    properties and reactions with hydroxyl radicals
    ANSWER 53 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Dehydrofluorination, fluorination, and decomposition of fluorohydrocarbons
TI
    with phosphate catalysts
               KIND DATE APPLICATION NO.
                                                             DATE
    PATENT NO.
                                      ----
                                                             _____
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    JP 08104656
                     A2 19960423 JP 1994-243024
                                                             19941006
PΙ
    ANSWER 54 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation of a substrate having a fluoride-doped conductive coating
TI
                 KIND DATE APPLICATION NO. DATE
    PATENT NO.
                                       ______
                      ____
    _____
    US 5496583 A 19960305 US 1994-297400 19940829 WO 9606958 A1 19960307 WO 1995-US10854 19950828
PΙ
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI,
            GB, GE, HU, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD,
            MG, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ,
            TM, TT
        RW: KE, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT,
            LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE,
            SN, TD, TG
                             19960322
                                        AU 1995-34959
                                                             19950828
    AU 9534959
                       A1
    ANSWER 55 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Four-component aerosol compositions
TI
                                       APPLICATION NO. DATE
    PATENT NO. KIND DATE
                      A1 19960111 WO 1994-US7426 19940630
    _____
    WO 9600564
PΙ
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, ES, FI, GB,
           GE, HU, JP, KE, KG, KP, KR, KZ, LK, LU, LV, MD, MG, MN, MW, NL,
           NO, NZ, PL, PT, RO, RU, SD, SE, SI, SK, TJ, TT, UA, UZ, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE,
            BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG
                       A1
                            19960125
                                     AU 1994-73206
    AU 9473206
    ANSWER 56 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Aerosol detergent compositions with low toxicity for cleaning automotive
    brakes
                     KIND DATE APPLICATION NO.
    PATENT NO.
                     ----
                      A2
                             19951219 JP 1994-126602
PΙ
    JP 07331290
                                                            19940608
    ANSWER 57 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Infrared photochemical properties of sensitized SO2-O2 mixtures
L4
    ANSWER 58 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
    Energy-saving binary refrigerant mixtures without ozone layer depletion
    effect
    PATENT NO.
                     KIND DATE
                                     APPLICATION NO.
                           19950125 CN 1993-109083
PΙ
    CN 1097792
                      Α
                                                            19930721
L4
    ANSWER 59 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Hair aerosol compositions containing polymers and dimethylether
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
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ΡI	EP 663203	A1	19950719	EP 1994-402874	19941213
	EP 663203	B1		TM IT NI CD	
				IT, LI, NL, SE FR 1994-367	19940114
	FR 2715064 FR 2715064	A1 B1			19940114
	AT 205698	E			19941213
	CA 2138481	AA			19941219
	CA 2138481	Ĉ	20020625	CA 1994 2130401	17711217
	HU 71747	A2	19960129	HU 1994-3827	19941229
	HU 218577	В		110 1991 302,	177.12027
	PL 177758	B1	20000131	PL 1994-306585	19941229
	KR 166391	B1	19990115		19941230
	BR 9500140	A			19950110
	CN 1113141	A		CN 1995-101243	19950113
	CN 1070358	В	20010905		
	JP 08040847	A2		JP 1995-4323	19950113
	JP 2834417	B2	19981209		
	RU 2124351	C1			
	US 6113923	Α	20000905	US 1995-372 395	19950113
L4	ANSWER 60 OF 214				
TI	_			cture of rigid foams	DAME
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
D.T.	TO 5201504	- А		US 1993-275 33	19930308
ΡI	US 5391584	A A	19950221	ZA 1992-1888	19920313
	ZA 9201888 ZA 9201895	A			19920313
	CN 1067435	A			19920327
	KR 227876	B1	19991101		19920327
	US 5238970	A	19930824		19921110
	US 5240965	A			
	US 5356556	Δ	19941018		19930514
	US 5368769	A A	19941129		19930527
	CN 1133854	Α	19961023	CN 1995-119 832	19951114
	CN 1048995	В	20000202		
L4	ANSWER 61 OF 214				
L4 TI	Refrigerating appa	ratus u	sing diflud	proethane-based refrigera	
	Refrigerating appa PATENT NO.	ratus u KIND	sing difluo DATE	proethane-based refrigera APPLICATION NO.	DATE
TI	Refrigerating appa PATENT NO.	ratus u KIND	sing difluo DATE	proethane-based refrigera APPLICATION NO.	DATE
	Refrigerating appa PATENT NO.	ratus u KIND	sing difluo DATE	proethane-based refrigera APPLICATION NO.	DATE
TI PI	Refrigerating appa PATENT NOJP 07027431	ratus u KIND A2	sing difluo DATE 19950127	oroethane-based refrigera APPLICATION NO. 	DATE
TI PI L4	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214	ratus u KIND A2 CAPLUS	sing difluon DATE 19950127 COPYRIGHT	oroethane-based refrigera APPLICATION NO. 	DATE 19930716
TI PI	Refrigerating appa PATENT NO. 	ratus u KIND A2 CAPLUS a coate	sing difluon DATE 19950127 COPYRIGHT	oroethane-based refrigera APPLICATION NO. 	DATE 19930716
TI PI L4	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues	ratus u KIND A2 CAPLUS a coate	sing difluo DATE 19950127 COPYRIGHT d substrate	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of	DATE 19930716 excited halogen
TI PI L4	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues	ratus u KIND A2 CAPLUS a coate	sing difluo DATE 19950127 COPYRIGHT d substrate	oroethane-based refrigeral APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing application NO.	DATE 19930716 excited halogen
TI PI L4 TI	Refrigerating appa PATENT NO. 	ratus u KIND A2 CAPLUS a coate KIND	sing difluon DATE 19950127 COPYRIGHT d substrate DATE	Proethane-based refrigers APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO.	DATE 19930716 excited halogen DATE
TI PI L4	Refrigerating appa PATENT NO. 	ratus u KIND A2 CAPLUS a coate KIND A1	sing difluon DATE 19950127 COPYRIGHT d substrate DATE	oroethane-based refrigeral APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing application NO.	DATE 19930716 excited halogen DATE
TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US	ratus u KIND A2 CAPLUS a coate KIND A1	sing difluon DATE 19950127 COPYRIGHT d substrate DATE 19950126	APPLICATION NO. 2006 ACS on STN with a gas containing of APPLICATION NO. APPLICATION NO. WO 1994-US7751	DATE 19930716 excited halogen DATE 19940712
TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D	sing difluct DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR,	Proethane-based refrigers APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO.	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE
TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1	sing difluon DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712
TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1	sing difluon DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508	APPLICATION NO. 2006 ACS on STN with a gas containing of APPLICATION NO. APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC,	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712
TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2	sing difluon DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS	sing difluct DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712
PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of electors	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS	sing difluct DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of electer polymers	ratus u KIND A2 CAPLUS a coate KIND A1 DE, D A1 T2 CAPLUS ctrical	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT dy conduction	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Te, soluble pyrrole-3-ca	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of electer polymers	ratus u KIND A2 CAPLUS a coate KIND A1 DE, D A1 T2 CAPLUS ctrical	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT dy conduction	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Te, soluble pyrrole-3-ca	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of elected ester polymers PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 DE, D A1 T2 CAPLUS ctrical KIND	sing difluctions DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conductions	APPLICATION NO. APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN ve, soluble pyrrole-3-cat	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of elected ester polymers PATENT NO. JP 06206986	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS ctrical KIND A2	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Te, soluble pyrrole-3-ca	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of elected ester polymers PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS ctrical KIND A2	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726	APPLICATION NO. APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN ve, soluble pyrrole-3-cat	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of elector polymers PATENT NO. JP 06206986 JP 3024867	ratus u KIND A2 CAPLUS a coate KIND A1 T2 CAPLUS ctrical KIND A2 B2	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327	oroethane-based refrigeral APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN To Strain STR	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI	Refrigerating appa PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 T2 CAPLUS CTICAL KIND A2 B2 CAPLUS	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327 COPYRIGHT	oroethane-based refrigeral APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN No. APPLICATION NO. JP 1992-180695	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE
PI L4 TI PI L4 TI	Refrigerating appa PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS ctrical KIND A2 B2 CAPLUS smoke KIND	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327 COPYRIGHT detectors as	APPLICATION NO. APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Twe, soluble pyrrole-3-cate APPLICATION NO. JP 1992-180695 2006 ACS on STN Ind their manufacture APPLICATION NO.	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE 19920708
PI L4 TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of eleester polymers PATENT NO. JP 06206986 JP 3024867 ANSWER 64 OF 214 Testing agents for PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS ctrical KIND A2 B2 CAPLUS smoke KIND	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327 COPYRIGHT detectors as DATE	oroethane-based refrigeral APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN No. APPLICATION NO. JP 1992-180695 2006 ACS on STN No. APPLICATION NO. JP 1992-180695	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE 19920708
PI L4 TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of eleester polymers PATENT NO. JP 06206986 JP 3024867 ANSWER 64 OF 214 Testing agents for PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 , DE, D A1 T2 CAPLUS ctrical KIND A2 B2 CAPLUS smoke KIND	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327 COPYRIGHT detectors as DATE	APPLICATION NO. APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Twe, soluble pyrrole-3-cate APPLICATION NO. JP 1992-180695 2006 ACS on STN Ind their manufacture APPLICATION NO.	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE 19920708
PI L4 TI PI L4 TI PI L4 TI	Refrigerating appa PATENT NO. JP 07027431 ANSWER 62 OF 214 Post treatment of to remove residues PATENT NO. WO 9502472 W: JP, KR, US RW: AT, BE, CH EP 710161 R: DE JP 09502646 ANSWER 63 OF 214 Manufacture of eleester polymers PATENT NO. JP 06206986 JP 3024867 ANSWER 64 OF 214 Testing agents for PATENT NO.	ratus u KIND A2 CAPLUS a coate KIND A1 T2 CAPLUS ctrical KIND A2 B2 CAPLUS smoke KIND A	sing difluction DATE 19950127 COPYRIGHT d substrate DATE 19950126 K, ES, FR, 19960508 19970318 COPYRIGHT ly conduction DATE 19940726 20000327 COPYRIGHT detectors a DATE 19940323	APPLICATION NO. JP 1993-176804 2006 ACS on STN with a gas containing of APPLICATION NO. APPLICATION NO. WO 1994-US7751 GB, GR, IE, IT, LU, MC, EP 1994-922123 JP 1994-504652 2006 ACS on STN Ve, soluble pyrrole-3-cate APPLICATION NO. JP 1992-180695 2006 ACS on STN and their manufacture APPLICATION NO. CN 1993-119728	DATE 19930716 excited halogen DATE 19940712 NL, PT, SE 19940712 19940712 arboxylic acid DATE 19920708

TI	Substance separate gas-mixture flows	ion by t through	he action of capillaries	a pulsed IR laser radi	lation on
L4 TI	ANSWER 66 OF 214 Manufacture of the PATENT NO.	armonlac	tic polyecter	r forms by extrusion	DATE
PI	JP 06145404 JP 2801483	A2 B2	19940524 19980921	APPLICATION NO. JP 1992-317764	19921102
L4 TI	ANSWER 67 OF 214 One-component syst dimensional stabil PATENT NO.	tem for :	preparation o	of rigid polyurethane f	DATE
ΡI	DE 4303887	A1	19940421	DE 1993-4303887	19930210
L4 TI	ANSWER 68 OF 214 Gaseous doping of PATENT NO.	tungste	n oxide	APPLICATION NO.	DATE
ΡI	US 5324537	Α	19940628	US 1993-86796	19930706
L4 TI	ANSWER 69 OF 214 Hydrofluorocarbon static magnetron			006 ACS on STN licon dioxide etch in a	an axisymmetric
L4 TI	ANSWER 70 OF 214 Manufacture of ser PATENT NO.	miconduc KIND	tor devices DATE	APPLICATION NO.	DATE
ΡI				JP 1992-1799 93	
L4 TI	ANSWER 71 OF 214 Manufacture of ser PATENT NO.	niconduc KIND	tor device by DATE	y plasma etching APPLICATION NO.	DATE
PI	JP 06021016	A2	19940128	JP 19 92-174114	19920701
L4 TI	ANSWER 72 OF 214 Manufacture of fle	exible p	olyurethane :	006 ACS on STN Foams having low densit APPLICATION NO.	DATE
PI				JP 1992-134 451	
L4 TI	PATENT NO.	rosol co KIND	mposition wit DATE	006 ACS on STN th high solid content APPLICATION NO.	
ΡΊ	CA 2093781 AU 9336751 AU 671104 EP 570085	AA A1 B2	19931017 19931021 19960815	CA 1993-2093 781 AU 1993-367 5 1	19930408 19930406
	BR 9301551 ZA 9302658	H, DE, D A A A	19931019 19941015 19970225	B, IE, IT, LI, LU, NL, BR 1993-1551 ZA 1993-2658 US 1994-2381 95	19930415 19930415
L4 TI		gas-chr	omatographic	006 ACS on STN retention parameters f physicochemical charac	
L4 TI	ANSWER 75 OF 214 Stabilized polyoxy PATENT NO.	yalkylen KIND	e glycols DATE	APPLICATION NO.	DATE
PI	WO 9217563	A1	19921015	WO 1992-US2 148	19920318

PL, RO, RU, SD RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, DE, DK, ES, FR, GA, GB, GN, GR, IT, LU, MC, ML, MR, NL, SE, SN, TD, TG AU 1992-17**754** 19920318 19921102 A1 AU 9217754 ANSWER 76 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4 Working fluids TT APPLICATION NO. DATE PATENT NO. KIND DATE ----______ ----------JP 05117646 19930514 JP 1991-281038 19911028 A2 PΙ ANSWER 77 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Working fluids ΤI APPLICATION NO. DATE PATENT NO. KIND DATE ____ ______ -----19930126 JP 1991-171032 JP 05017743 A2 19910711 PΙ ANSWER 78 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Working fluids TΤ APPLICATION NO. DATE KIND DATE PATENT NO. ---------_____ -----19930126 JP 1991-171035 **1991071**1 A2 PΙ JP 05017746 ANSWER 79 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Working fluids ΤI APPLICATION NO. DATE PATENT NO. KIND DATE _____ ----------____ 19930126 JP 1991-172368 19910712 JP 05017748 PΙ A2 ANSWER 80 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN T.4 Working fluids TΤ APPLICATION NO. DATE PATENT NO. KIND DATE _____ -----______ ----19930126 JP 1991-172**371** JP 05017751 A2 19910712 PΙ ANSWER 81 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Working fluids PATENT NO. TΤ APPLICATION NO. DATE KIND DATE ----______ ----**---**JP 05017755 A2 19930126 JP 1991-172375 19910712 PΙ ANSWER 82 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Working fluids ΤI APPLICATION NO. DATE KIND DATE PATENT NO. ____ ----------JP 05017758 A2 19930126 JP 1991-1723**78** PT · 19910712 ANSWER 83 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN T.4 Prediction of refrigerant thermodynamic properties by equations of state: TΙ vapor liquid equilibrium behavior of binary mixtures ANSWER 84 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Crosslinked polyolefin foaming compositions TΙ PATENT NO. KIND DATE APPLICATION NO. DATE ____ -----A2 19920602 JP 1990-283331 PΙ JP 04159339 19901023 ANSWER 85 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN T.4 тΤ Performance-oriented packaging standards; changes to classification, hazard communication, packaging and handling requirements based on UN standards and agency initiative ANSWER 86 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Manufacture of expandable vinylidene chloride resin particles TΙ PATENT NO. KIND DATE APPLICATION NO. DATE ----

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JP 03223346

A2 19911002 JP 1990-17733 19900130

W: AU, BB, BG, BR, CA, CS, FI, HU, JP, KP, KR, LK, MG, MN, MW, NO,

L4 TI	ANSWER 87 OF 214 Multivariate mode haloalkanes with	eling of	the rate co	onstant of the gas-phase	e reaction of
L4 TI				2006 ACS on STN ldings for thermal insul	lators of
	refrigerators PATENT NO.	KIND		APPLICATION NO.	DATE
PI	JP 03225182			JP 1990-17732	
L4 TI	ANSWER 89 OF 214 Preparation of the PATENT NO.	nermally KIND	insulating	urethane foams APPLICATION NO.	DATE
PI				JP 1989-276342	
L4 TI	ANSWER 90 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.			APPLICATION NO.	DATE
PI	JP 03220285 JP 2532736	A2 B2	19910927 19960911	JP 1990-242 13 1	19900911
L4 TI	ANSWER 91 OF 214 Combustion-engine non-ozone-damagir	ering sa	afety data o	2006 ACS on STN of the material pair R15 onventional refrigerants	52A/R134A as a 3
L4	ANSWER 92 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Working fluids PATENT NO.	KIND		APPLICATION NO.	DATE
PI	JP 03170583	A2	19910724	JP 1989-311149 US 1993-125146	19891130
L4 TI	ANSWER 93 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
**	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 03168271	A2	19910722		19891129
L4 TI	ANSWER 94 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 03170593	A2	19910724	JP 1989-311164	19891130
L4 TI	ANSWER 95 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.			APPLICATION NO.	
ΡI				JP 1989-3111 63 US 1993-1251 46	
L4 TI	ANSWER 96 OF 214 Working fluids				
	PATENT NO.				
PI		B2	19970212	JP 1989-311160 US 1992-839700	
T 4	US 5304319				17320224
L4 TI	ANSWER 97 OF 214 Working fluids PATENT NO.	KIND	DATE		DATE
DТ				JP 1989-311159	
ΡI	JP 03170589	A2	19910/24	OR 1383-3111 53	19891130

ANSWER 98 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

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TI	Working fluids PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03168261		19910722	JP 1989-309640	19891129
L4 TI	ANSWER 99 OF 214 Working fluids	CAPLUS	COPYRIGHT 20	006 ACS on STN	
-	PATENT NO.	KIND		APPLICATION NO.	DATE
PI	JP 03168287			JP 1989-309669	
L4 TI	ANSWER 100 OF 214 Working fluids	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
	PATENT NO.	KIND	DATE		DATE
PI	JP 03168290				
L4 TI				2006 ACS on STN foaming solutions witho	out ozone
	layer depletion PATENT NO.	KIND		APPLICATION NO.	DATE
PI		A2	19910626	JP 1989-2897 29	
L4	ANSWER 102 OF 214				
TI	Apparatus for man	KIND	DATE	arethane solutions APPLICATION NO.	DATE
ΡI	JP 03150108 JP 2706991	A2	19910626	JP 1989-289728	19891106
L4 TI	ANSWER 103 OF 214 Semiempirical cal silicon inner cor	culation	of ESCA shif	fts in oxygen, <mark>nitrogen,</mark>	fluorine and
L4 TI	ANSWER 104 OF 214 Aerosol composition				
11		KIND	DATE	APPLICATION NO.	DATE
PI	EP 423695	A2	19910424	EP 1990-119769	
	EP 423695 R: AT, BE, C			B, GR, IT, LI, NL, SE	
	AU 9064634	A1	19910426	AU 1990-6463 4	19901015
	NO 9004492	A	19910422	NO 1990-4492	19901017
	CA 2027952		40040400	GT 1000 000000	10001017
		AA NO	19910420	CA 1990-2027 952	19901018
	JP 03255023 US 5378451	AA A2 A	19910420 19911113 19950103	CA 1990-2027 952 JP 1990-2816 90 US 1993-1267 47	19901018 19901019 19930927
L4	ANSWER 105 OF 214	CAPLUS	COPYRIGHT 2	CA 1990-2027 952 JP 1990-2816 90 US 1993-1267 47 2006 ACS on STN	19901018 19901019 19930927
L4 TI	ANSWER 105 OF 214 Etching of semico	CAPLUS nductor w	COPYRIGHT 2	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas	19901018 19901019 19930927
	ANSWER 105 OF 214 Etching of semicor PATENT NO.	CAPLUS nductor w KIND	COPYRIGHT 2 ith fluoride DATE	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO.	19901018 19901019 19930927 DATE
TI	ANSWER 105 OF 214 Etching of semicor PATENT NO.	CAPLUS nductor w KIND	COPYRIGHT 2 with fluorided DATE	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO.	19901018 19901019 19930927 DATE
	ANSWER 105 OF 214 Etching of semicor PATENT NO. JP 03083335	CAPLUS nductor w KIND A2	COPYRIGHT 2 vith fluoride DATE 19910409	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO. JP 1989-218530	19901018 19901019 19930927 DATE
TI	ANSWER 105 OF 214 Etching of semicor PATENT NO. JP 03083335 EP 497023 R: DE, FR, G	CAPLUS nductor w KIND A2 A1	COPYRIGHT 2 with fluoride DATE 19910409 19920805	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN and hydrocarbon gas APPLICATION NO. JP 1989-218530 EP 1991-300793	19901018 19901019 19930927 DATE 19890828 19910131
TI	ANSWER 105 OF 214 Etching of semicor PATENT NO. JP 03083335 EP 497023	CAPLUS nductor w KIND A2 A1	COPYRIGHT 2 with fluoride DATE 19910409 19920805	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO. JP 1989-218530	19901018 19901019 19930927 DATE 19890828 19910131
TI	ANSWER 105 OF 214 Etching of semicor PATENT NO. JP 03083335 EP 497023 R: DE, FR, GR US 5110408 ANSWER 106 OF 214 Preparation of rig PATENT NO.	CAPLUS nductor w KIND A2 A1 B A CAPLUS gid polyu KIND	COPYRIGHT 2 with fluoride DATE 19910409 19920805 19920505 COPYRIGHT 2 arethane foam	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO. JP 1989-218530 EP 1991-300793 US 1991-658254 2006 ACS on STN as with low thermal cond APPLICATION NO.	19901018 19901019 19930927 DATE 19890828 19910131 19910220 Ructivity DATE
TI PI L4	ANSWER 105 OF 214 Etching of semicor PATENT NO. JP 03083335 EP 497023 R: DE, FR, Gr US 5110408 ANSWER 106 OF 214 Preparation of rightent No. EP 421269 EP 421269 EP 421269 EP 421269 EP 421269	CAPLUS nductor w KIND A2 A1 B A CAPLUS gid polyu KIND A2 A3 B1 B2	COPYRIGHT 2 vith fluoride DATE 19910409 19920805 19920505 COPYRIGHT 2 crethane foam DATE 19910410 19910904 19960110 20020502	CA 1990-2027952 JP 1990-281690 US 1993-126747 2006 ACS on STN e and hydrocarbon gas APPLICATION NO. JP 1989-218530 EP 1991-300793 US 1991-658254 2006 ACS on STN ns with low thermal cond	19901018 19901019 19930927 DATE 19890828 19910131 19910220 Ructivity DATE

	US 5096933	Α	19920317	US 1990-5771 74	19900904
	US 5096933	B1	19960326		
		AA	19910407	CA 1990-2024 714	19900906
	CA 2024714	C	19980623	7 M 1000 110533	10000007
	AT 132882	E T3	19960115 19960316	AT 1990-118532 ES 1990-118532	19900927 19900927
	ES 2081887	T3 A2	19960316	JP 1990-266573	
		B2	19910628 20011009	JP 1990-266573	19901005
	JP 3216646 KR 173981	B2 B1	19990401	KR 1990-15963	19901006
	RR 173961	ъī	19990401	RR 1990-13903	13301000
L4 TI	ANSWER 107 OF 214 Working fluid	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	EP 430170	A1	19910605	EP 1990-122653	19901127
	EP 430170	B1	19940803		
	R: DE, FR, GB				
	JP 03170584	A2 B2	19910724	JP 1989-3111 53	19891130
	JP 2532695	B2	19960911		
	JP 03170587		19910724	JP 1989-3111 56	19891130
	JP 2532696	B2	19960911		
L4 TI	ANSWER 108 OF 214 Working fluid	CAPLUS	COPYRIGHT	2006 ACS on STN	
11		KIND	DATE	APPLICATION NO.	DATE
ΡI	EP 430171	A1	19910605	EP 1990-122654	
	EP 430171	B1	19931006		2330222,
	R: DE, FR, GB				
	JP 03172384	A2	19910725	JP 1989-3111 66	19891130
	JP 2532697	B2	19960911		
	JP 03172386	A2	19910725	JP 1989-3 11168	19891130
	JP 2548412	B2	19961030		
L4	ANSWER 109 OF 214				
TI	Catalytic hydrodecl	nlorinat	ion of freo	n 113, (CFC 11 <mark>3, CCl2FC</mark>	ClF2)
L4	ANSWER 110 OF 214				
TI				enhanced sputtering of	
					DATE
DT		7.1	10000007	WO 1000 HGC77	10000000
ΡI	WO 9010303 WO 9010303			WO 1990-US677	19900206
	W: JP, KP	A3	19901018		
		את שת	FC FD C	B, IT, LU, NL, SE	
	US 5089746	A	, 65, FR, G. 19920218	US 1989-311504	19890214
	05 3003740	A	17720210	03 1909 311904	13030214
L4	ANSWER 111 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
				ght metal fluorides	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI					
	EP 400796	B1	19940316	EP 1990-3040 73	
	R: DE, FR, GB				
	CA 2015802	AA	19901130	CA 1990-2015 802	19900501
	JP 03017601	A2	19910125	JP 1990-1395 60	19900529
	US 5208101	Α	19930504		19910701
L4					
TI	Manufacture of flam	ne-retar		e resin laminar foams	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
n ~	TD 00100-10				
ΡI				JP 1988-2744 31	19881101
	JP 06045719	В4	19940615		
	ANSWER 113 OF 214	CA DI IIO	CODVETCUE	2006 200 000	
L4					

L4 ANSWER 113 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Laser induced nonstationary processes in gaseous mixtures through porous media

L4	ANSWER 114 OF 214				
TI	Combining a blowin polyurethane foam PATENT NO.	manufact	ure DATE	st one liquid reaction APPLICATION NO.	DATE
ΡI	DE 3819630 EP 345580	A1 A2	19891214 19891213	DE 1988-3819630 EP 1989-109610	19880609 19890527
	R: AT, BE, CH JP 02039921	, DE, ES	, FR, GB, I	Г, LI, NL, SE JP 1989-1432 03	
L4 TI	ANSWER 115 OF 214 Heat pumps with fl PATENT NO.			fluids	DATE
PI	JP 01200153			JP 1988-25011	19880204
L4 TI	ANSWER 116 OF 214 Process for restor aromatic compound	ing deac producti	tivated Grown	up VIII element-zeolite	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI		A1 B1	19890524 19920122	EP 1988-118621	
	US 4937215	Α	19900626	US 1988-2566 97	
				CA 1988-580 661 JP 1988-28 0348	
					13001100
L4 TI	ANSWER 117 OF 214 Pyrolytically coat				
11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	DE 3823089	 A1		DE 1988-3823089	19880707
	GB 2206878	A1	19890118	GB 1987-16 388	19870711
		B2	19910717	EC 1000 1707	19880608
	BE 1002216	A6 A4	19901016	ES 1988-1782 BE 1988-683	19880615
	FR 2617833	A1	19890113	FR 1988-8210	19880616
	FR 2617833 AT 8801725	B1 A	19920417	AT 1988-1725	19880704
		A	19890201	NL 1988-1713	19880707
	CH 675416	Α	19900928	CH 1988-2595	19880707
		Α	19890112	SE 1988-2578	
	SE 465921	A B C	19911118		
	SE 465921	C A2	19920312	JP 1988-170 751	10000700
					19880/08
L4 TI	ANSWER 118 OF 214 Multilayer heat in				
1.1	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI				JP 1986-297 088	
L4 TI	ANSWER 119 OF 214			2006 ACS on STN L sensors from biofouli	ng in an
1.1	aquatic environmen PATENT NO.	t		APPLICATION NO.	_
ΡI	US 4763537	A	19880816	US 1986-941 774	19861215
L4 TI	ANSWER 120 OF 214 Laser action on re			2006 ACS on STN bws through capillaries	
L4	ANSWER 121 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI	Aerosol waterproof	sunscre	en compositi		DATE
ΡĪ				US 1985-807488	
	· · · · · · ·		· 	· - - • •	

	GB 2202740	A1	19881005	GB 1987-7617	19870331
	GB 2202740				
L4	ANSWER 122 OF 214	CAPLUS	COPYRIGHT :	2006 ACS on STN	
TI	Improvement of the	hydroly	tic resista	nce of bottles by sur	face treatment
L4	ANSWER 123 OF 214			2006 ACS on STN	
TI	Manufacture of hol PATENT NO.			APPLICATION NO.	DATE
ΡI	JP 62117813	A2	19870529	JP 1985-255018	19851115
L4	ANSWER 124 OF 214				
TI	Laser action on ga	s mixtur	re flows thro	ough metal capillaries	3
L4	ANSWER 125 OF 214		COPYRIGHT 2	2006 ACS on STN	
TI	Silica film etching PATENT NO.	KIND		APPLICATION NO.	
ΡI	JP 61251138			лр 1985-9302 4	
					13030130
L4 TI	ANSWER 126 OF 214 Effect of laser ra			2006 ACS on STN age of resonan ce mole c	cules through
	capillaries in a t				, <u> </u>
L4	ANSWER 127 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI	Semiconductor devi-		DAME	APPLICATION NO.	DATE
		KIND 			DATE
PI	JP 60143633 JP 61004179	A2 B4	19850729 19860207	JP 1984-250543	19841129
L4 TI	ANSWER 128 OF 214 Nonflammable aeros				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 4536323			US 1983-508643	
	CA 1205349	A1	19860603	CA 1984-457 246 AU 1984-3308 3	19840622
	AU 574715 AU 8433083				19840917
				US 1985-749 962	19850701
L4	ANSWER 129 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI				of silicon nitride	D3.000
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3420347	A1	19841206	DE 1984-342 0347	19840530
	DE 3420347	Δ2	19870820	JP 1983-956 51	19830601
	JP 60115232	A2	19850621	JP 1983-222 072	19831128
	NL 8401774	Α	19850102	NL 1984-1774	19840601
	US 4529476	Α	19850716	JP 1983-222 072 NL 1984-1774 US 1984-616 114	19840601
L4	ANSWER 130 OF 214				
TI	Limit of thermal is	gnition	for a light-	-initiated unbranched	chain reaction
L4	ANSWER 131 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI				teraction pot ential of	: polar
L4	ANSWER 132 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI		ım gas o	ils with cat	alyst and an added or	ganic fluorine
	compound PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DT				US 1981-301 754	
ΡΙ	JP 59202291	A A2	19831213 19841116	JP 1983-77342	19830430

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ΤI	_	_		resin composition		
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE	
ΡI	GB 2110216	A1	19830615	CB 1982-32528	19821115	
	JP 58084832	A2	19830521	JP 1981-183 349	19811116	
	JP 62017613	B4	19870418			
	JP 58087135	A2	19830524	JP 1981-1859 68	19811119	
	JP 02030341	B4	19900705			

- L4 ANSWER 134 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of vinyl chloride, trifluorochloroethylene, difluoroethane, hexafluoropropylene, and hexafluoropropylene oxide in water
- L4 ANSWER 135 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Viscosity of difluoroethane
- L4 ANSWER 136 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Specification and usage requirements for 3AL seamless, aluminum cylinders
- L4 ANSWER 137 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

ΤI	Fluorination	of	catalyst	cs
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11	riudiliacion di ca	icaryscs			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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ΡI	GB 2024642	A	19800116	GB 1979-2333 8	19790704
	GB 2024642	B2	19820818		
	FR 2430263	A1	19800201	FR 1978-2018 2	19780706
	FR 2430263	B1	19810102		
	CA 1137062	A1	19821207	CA 1979-326 392	19790426
	NL 7905206	Α	19800108	NL 1979-5206	19790704
	DE 2927052	A1	19800117	DE 1979-292 7052	19790704
	JP 55011097	A2	19800125	JP 1979-840 50	19790704
	JP 62052623	B4	19871106		

- L4 ANSWER 138 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solvent effects on the distribution coefficients. III. The solubility of some lower fluoro- and chlorohydrocarbons in organic solvents
- L4 ANSWER 139 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of gas-kinetic diameters of molecules of difluoroethane and fluoro-substituted derivatives of ethylene
- L4 ANSWER 140 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of the gas-kinetic diameters of molecules of difluoroethane and fluorine-substituted derivatives of ethylene
- L4 ANSWER 141 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 142 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Study of the thermal conductivity of toluene and some difluoroethanes at high pressures
- L4 ANSWER 143 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VIII. Respiration and circulation in primates
- L4 ANSWER 144 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 145 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VI. Influence of cardiac and pulmonary vascular lesions in the rat
- L4 ANSWER 146 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Cardiopulmonary toxicity of propellants for aerosols

- L4 ANSWER 147 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of chlorine, hydrogen chloride, difluoro- and difluorochloroethanes in chloroorganic solvents
- L4 ANSWER 148 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants on the respiratory and circulatory systems. III. Influence of bronchopulmonary lesion on cardiopulmonary toxicity in the mouse
- L4 ANSWER 149 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. IV. Cardiotoxicity in the monkey
- L4 ANSWER 150 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Identification of absorption lines in gases used to modulate the carbon dioxide laser
- L4 ANSWER 151 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Thermal energy electron attachment rate constants for some polyatomic molecules
- L4 ANSWER 152 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Regeneration of hydrocracking catalysts

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
		-			
ΡI	DE 2249892	A1	19730419	DE 1972-2249892	19721011
	US 3725244	Α	19730403	US 1971-1884 08	19711013

- L4 ANSWER 153 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hydrocracking catalyst activation treatment

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PΙ	US 3673108	Α	19720627	US 1969-8896 81	19691231

- L4 ANSWER 154 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- Homopolymers and copolymers of vinylidene fluoride

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-			
FR 1570233		19690606	FR	
DE 1770672			DE	
GB 1188889			GB	
US 3616371		19710000	US	

- L4 ANSWER 155 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Metal oxide films

PΙ

11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 1167128		19691015	GB	
	FR 1572757			FR	
	US 3477936		19690000	US	

- L4 ANSWER 156 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Gas-chromatographic analysis of aerosols by pressurized liquid sampling
- L4 ANSWER 157 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hair waving, two phase, quick breaking, aerosol foam
 PATENT NO. KIND DATE APPLICATION NO. DATE

 PI US 3433868 A 19690318 US 1964-385467 19640727
- L4 ANSWER 158 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Concentration of sea water and brine by the gas hydration process. XIV. Pressure and temperature diagrams of mixed hydrating agents
- L4 ANSWER 159 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Careful removal of acetylene and difluroethane from vinyl fluoride
- L4 ANSWER 160 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Studies on explosions. I

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ANSWER 161 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Conversion of hydrocarbons by hydrogen
TI
                                    APPLICATION NO.
                KIND DATE
    PATENT NO.
                                                             DATE
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                                                              _____
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                                                              19620408
    FR 1349148
                             19640117
PΙ
    ANSWER 162 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Effect of anions on the electrocrystallization of zinc and cadmium
TI
    ANSWER 163 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    The electrochemical fluorination of organosilicon compounds
ТT
    ANSWER 164 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant mixture of dichlorodifluoromethane and difluoroethane
TI
               KIND DATE APPLICATION NO. DATE
    PATENT NO.
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                             _____
                                        ______
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                             19510417 US
    US 23358
PΤ
    ANSWER 165 OF 214 USPATFULL on STN
L4
      Materials and methods for the conversion of hydrofluorocarbons
TI
      US 2005288536 A1 20051229
PI
    ANSWER 166 OF 214 USPATFULL on STN
L4
      Process for making polyurethane and polyisocyanurate foams using
TI
      mixtures of a hydrofluorocarbon and methyl formate as a blowing agent
PΙ
      US 2005277701
                     A1 20051215
    ANSWER 167 OF 214 USPATFULL on STN
L4
TI
      Topical spray compositions
                  B1 20051108
ΡI
      US 6962691
    ANSWER 168 OF 214 USPATFULL on STN
T<sub>1</sub>4
      Heat transfer fluids and methods of making and using same
TI
PΙ
      US 2005218371 A1 20051006
    ANSWER 169 OF 214 USPATFULL on STN
L4
      Refrigerant composition
TI
PΤ
      US 2005109977 A1 20050526
    ANSWER 170 OF 214 USPATFULL on STN
1.4
      Closed cycle refrigeration system and mixed component refrigerant
ΤI
                     A1 20050428
ΡI
      US 2005086950
    ANSWER 171 OF 214 USPATFULL on STN
L4
ΤI
      Etchant with selectivity for doped silicon dioxide over undoped silicon
      dioxide and silicon nitride, processes which employ the etchant, and
      structures formed thereby
      US 6875371
                       B1 20050405
PΤ
    ANSWER 172 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
TI
PI .
      US 2004227125 A1 20041118
    ANSWER 173 OF 214 USPATFULL on STN
L4
TI
      Topical spray compositions
                     A1 20041028
ΡI
      US 2004213744
    ANSWER 174 OF 214 USPATFULL on STN
T.4
TI
      Formulations of mometasone and a bronchodilator for pulmonary
      administration
PΤ
      US 2004198708
                      A1 20041007
    ANSWER 175 OF 214 USPATFULL on STN
L4
ΤI
      Sol-gel-derived halogen-doped glass
PΙ
      US 2004194511 A1 20041007
    ANSWER 176 OF 214 USPATFULL on STN
T.4
ΤI
      Materials and methods for the conversion of hydrofluorocarbons
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20040701
PΙ
                         Δ1
       US 2004127757
     ANSWER 177 OF 214 USPATFULL on STN
L4
       Method for plasma etching performance enhancement
ΤI
                     A1
                               20040415
PΤ
       US 2004072443
                         В2
                               20041221
       US 6833325
     ANSWER 178 OF 214 USPATFULL on STN
L4
       Methods for etching photolithographic reticles
TI
                               20040415
       US 2004072081
                       A1
PΙ
     ANSWER 179 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
ΤI
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
                               20031030
PΙ
       US 2003203639
                         A1
     ANSWER 180 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TT
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
                               20030325
PΙ
       US 6537922
                         B1
     ANSWER 181 OF 214 USPATFULL on STN
L4
       Variable load refrigeration system particularly for cryogenic
TI
       temperatures
       US 6426019
                          B1
                               20020730
PΤ
     ANSWER 182 OF 214 USPATFULL on STN
T.4
       Formulations of mometasone and a bronchodilator for pulmonary
TI
       administration
       US 2002076382
                        A1 20020620
ΡI
     ANSWER 183 OF 214 USPATFULL on STN
T.4
       Substrate cleaning apparatus and method
ΤI
                       A1
       US 2002072016
                              20020613
PΙ
       US 6692903
                         B2
                               20040217
L4
     ANSWER 184 OF 214 USPATFULL on STN
       Apparatus for providing ozonated process fluid and methods for using
TI
       same
                        A1 20020606
PΙ
       US 2002066717
     ANSWER 185 OF 214 USPATFULL on STN
L4
       Lubricant refrigerant composition for hydrofluorocarbon (HFC)
TТ
       refrigerants
       US 6374629
PΙ
                         B1
                               20020423
     ANSWER 186 OF 214 USPATFULL on STN
L4
       High-density plasma etching of carbon-based low-k materials in a
TI
       integrated circuit
PΙ
      US 6284149
                         В1
                              20010904
     ANSWER 187 OF 214 USPATFULL on STN
T.4
       Flower-like capacitor structure for a memory cell
TΤ
PΤ
       US 6281542
                        B1 20010828
     ANSWER 188 OF 214 USPATFULL on STN
T.4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TТ
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
ΡI
      US 6117791
                               20000912
     ANSWER 189 OF 214 USPATFULL on STN
L4
      Aerosol cosmetic compositions, aerosols containing them and uses
ТI
ΡI
      US 6113923
                              20000905
    ANSWER 190 OF 214 USPATFULL on STN
L4
ΤI
       Fluorine assisted stripping and residue removal in sapphire downstream
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plasma asher PΙ US 6082374 20000704 ANSWER 191 OF 214 USPATFULL on STN T.4 Variable load refrigeration system particularly for cryogenic ΤI temperatures 20000620 PΤ US 6076372 ANSWER 192 OF 214 USPATFULL on STN L4 Process for the reduction of chlorofluorocarbons and production of ΤI derivatives thereof in an electrolytic cell, cell for carrying out said reduction and process for removing the by-products formed within the cell US 6068756 20000530 PΤ WO 9724162 19970410 ANSWER 193 OF 214 USPATFULL on STN L4Fixative vinyl acetate tetrapolymers TΙ US 5830439 19981103 PΙ ANSWER 194 OF 214 USPATFULL on STN L4 Method for etching dielectric using fluorohydrocarbon gas, NH.sub.3 TI -generating gas, and carbon-oxygen gas 19980929 US 5814563 PΙ ANSWER 195 OF 214 USPATFULL on STN L4Spray formulation for the testing of smoke detectors ΤI 19980728 US 5785891 PΙ ANSWER 196 OF 214 USPATFULL on STN L4Antiperspirant aerosol composition with high solids content ΤI PΙ US 5605682 19970225 ANSWER 197 OF 214 USPATFULL on STN L4 Hydrogen fluoride dopant source in the preparation of conductive coated TI substrate US 5496583 PΙ 19960305 ANSWER 198 OF 214 USPATFULL on STN L4ΤI Working fluid containing difluoroethane PΙ US 5433879 19950718 ANSWER 199 OF 214 USPATFULL on STN L4TI Manufacture of rigid foams and compositions therefor PΙ US 5391584 19950221 ANSWER 200 OF 214 USPATFULL on STN L4 Topical medicinal pressurized aerosol compositions and method of TΙ preparation, method of use and article of manufacture thereof PΙ US 5378451 19950103 ANSWER 201 OF 214 USPATFULL on STN L4 Gaseous doping of tungsten oxide TI PΙ US 5324537 19940628 ANSWER 202 OF 214 USPATFULL on STN T.4 TΤ Working fluid PΤ US 5304319 19940419 ANSWER 203 OF 214 USPATFULL on STN TI Anti-reflective coatings comprising light metal fluorides US 5208101 19930504 PΙ ANSWER 204 OF 214 USPATFULL on STN L4Process for etching TI ΡI US 5110408 19920505 L4 ANSWER 205 OF 214 USPATFULL on STN TT Process for the preparation of polyurethane rigid foams having a low

thermal conductivity and their use PΙ US 5096933 19920317 ANSWER 206 OF 214 USPATFULL on STN L4 Production of ion beams by chemically enhanced sputtering of solids TI19920218 PΙ US 5089746 ANSWER 207 OF 214 USPATFULL on STN L4 Process for restoring deactivated catalysts ΤI 19900626 US 4937215 PΙ ANSWER 208 OF 214 USPATFULL on STN L4 Process for protecting electrochemical sensors from biofouling in an ŢΙ aquatic environment US 4763537 19880816 PΙ ANSWER 209 OF 214 USPATFULL on STN L4Aerosol waterproof sunscreen compositions TI US 4686099 19870811 PΙ ANSWER 210 OF 214 USPATFULL on STN L4Preparation of non-flammable aerosol propellant microemulsion system ΤI US 4655959 19870407 ΡI ANSWER 211 OF 214 USPATFULL on STN L4Non-flammable aerosol propellant microemulsion system TI 19850820 US 4536323 PΙ ANSWER 212 OF 214 USPATFULL on STN L4Gas for selectively etching silicon nitride and process for selectively TI etching silicon nitride with the gas 19850716 PΙ US 4529476 ANSWER 213 OF 214 USPATFULL on STN **L4** Hydrotreating vacuum gas oils with catalyst and added organic fluorine ΤI compound US 4420388 19831213 PΙ ANSWER 214 OF 214 USPATFULL on STN L4HYDROCRACKING CATALYST ACTIVATION TREATMENT ΤI

19720627

PΙ

US 3673108